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“Predicting Circuit ESD Performance Through SPICE-type Simulations”

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Proprietary Information





MOTIVATION

- ◆ **ESD high on Pareto chart of reliability product returns from customers**

- ◆ **Predicting ESD performance is very compelling:**
 - 1) Design tool prior to manufacturing
 - 2) Design verification
 - 3) *Post-mortem* failure troubleshooting tool



OUTLINE

- ◆ **What is ESD?**
- ◆ **Circuit Simulation Consideration**
- ◆ **Compact Modeling Approaches and Modeling Verification**
- ◆ **ESD Circuit Simulation Examples**
- ◆ **Concluding Remarks**

What is ESD?

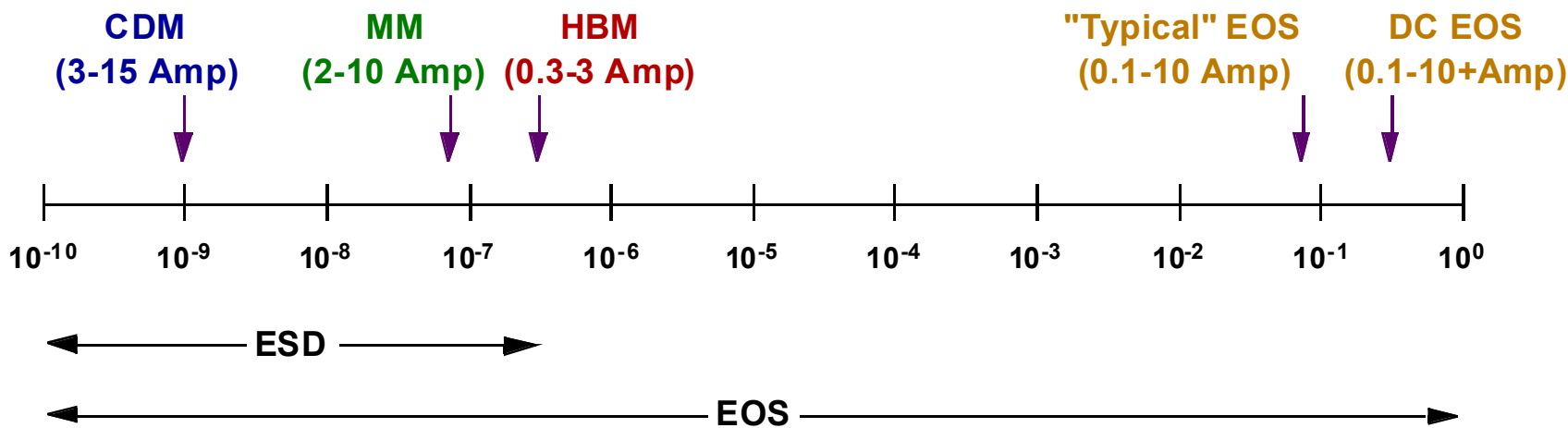
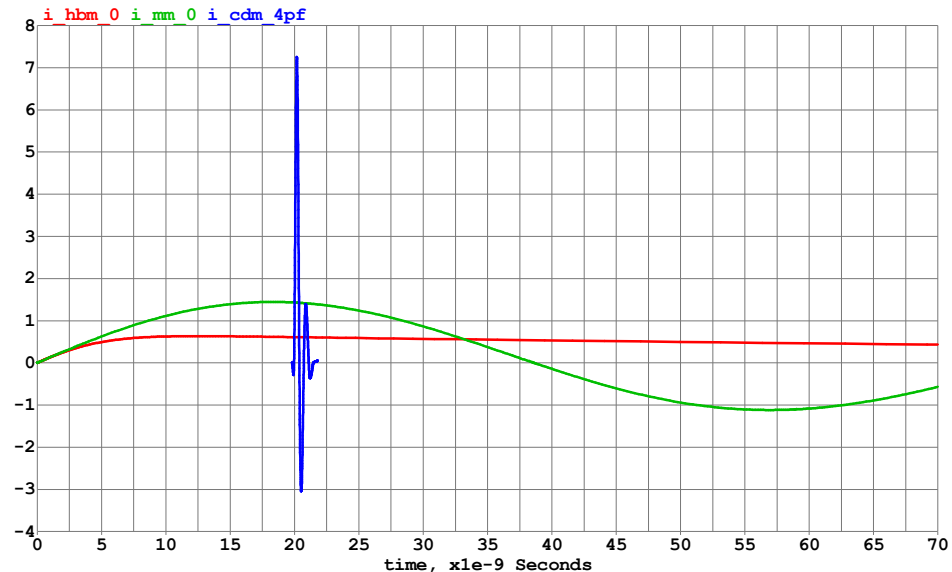
- ◆ **ESD: Electrostatic Discharge**
- ◆ **Cause: Tribo-electric charge transfer**
- ◆ **Characteristics**
 - **High energy resulting**
 - ◆ Large currents
 - ◆ High voltages
 - **Short in duration (typically <1 to over 100 nano-seconds)**



from RTP Company, Winona, MN

SOURCE of ESD

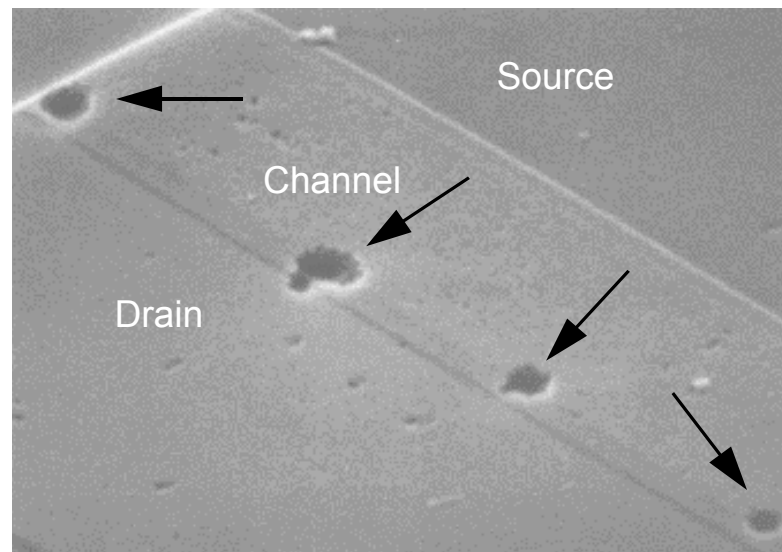
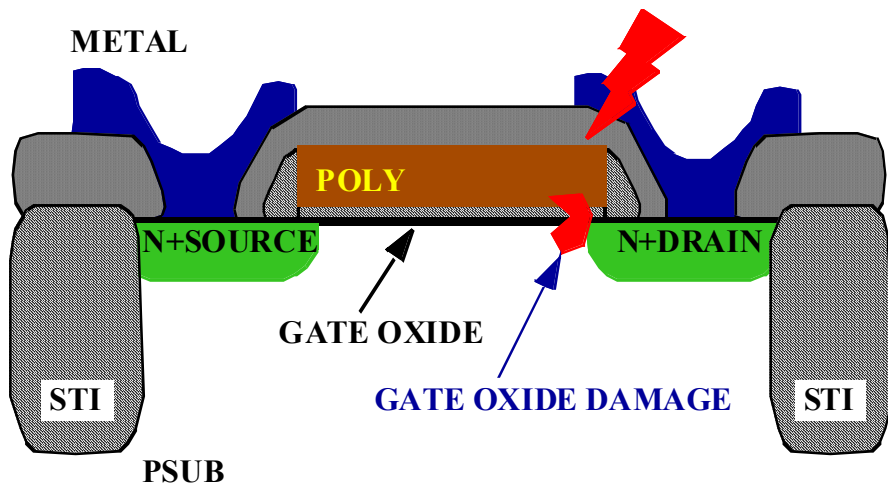
- ◆ Human touches IC: Human Body Model (**HBM**)
- ◆ Charged IC touches grounded surface: Charged Device Model (**CDM**)
- ◆ Charged machine touches IC: Machine Model (**MM**)



TIME in SECONDS (LOG SCALE)
 —Analog Devices Proprietary Information—

ESD DAMAGE in ICs (1)

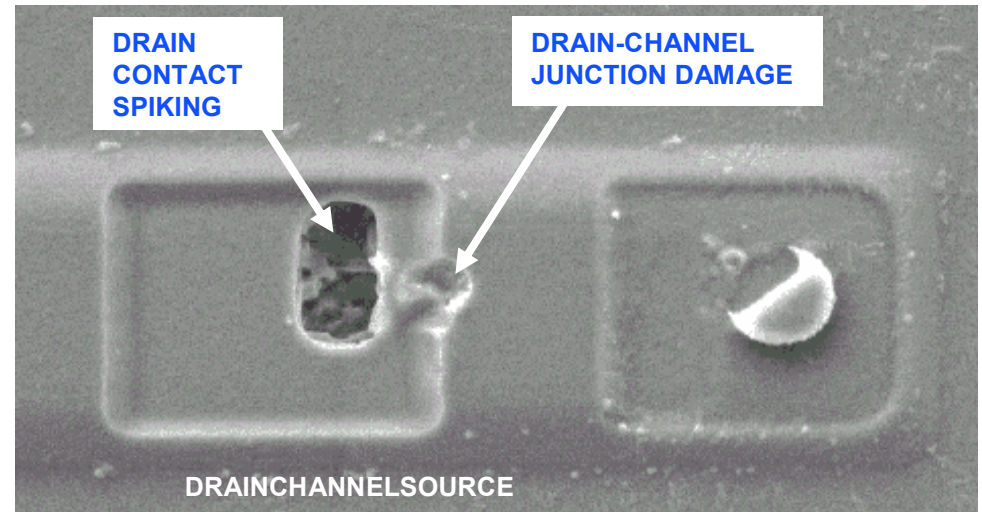
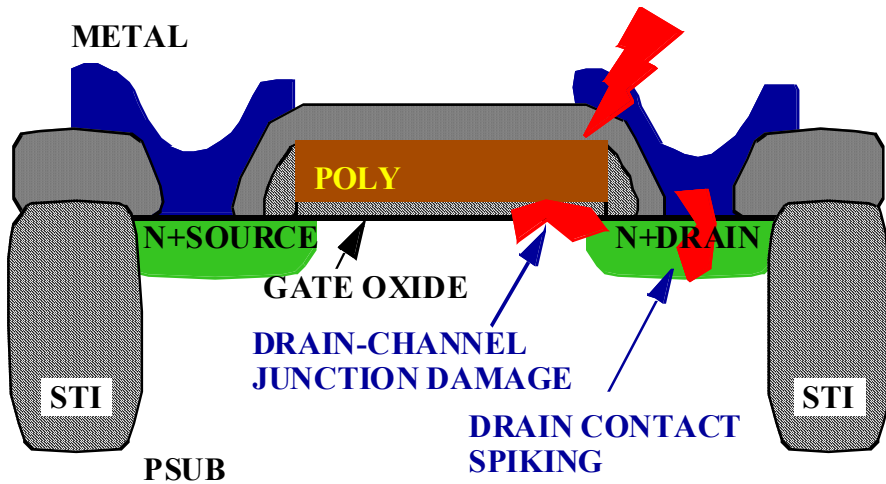
MOSFET Gate-Oxide Punch-through



- SEM micrograph depicts NMOS after de-processing.
- Pits are 0.2 to 0.5 μm in width & correspond to regions where Si flowed into gate oxide.

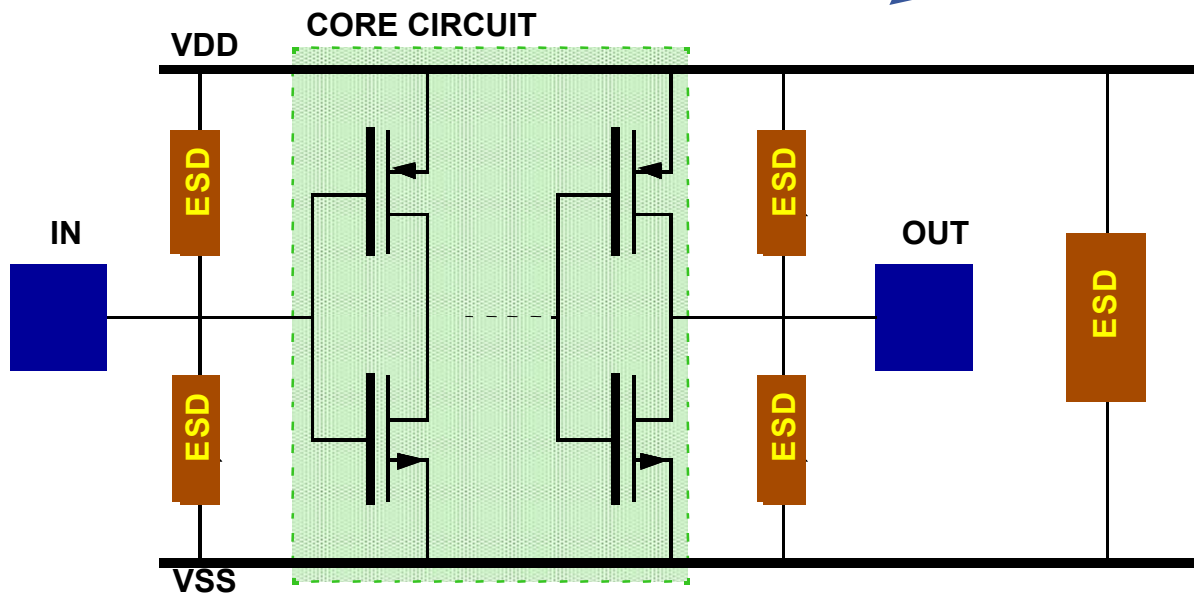
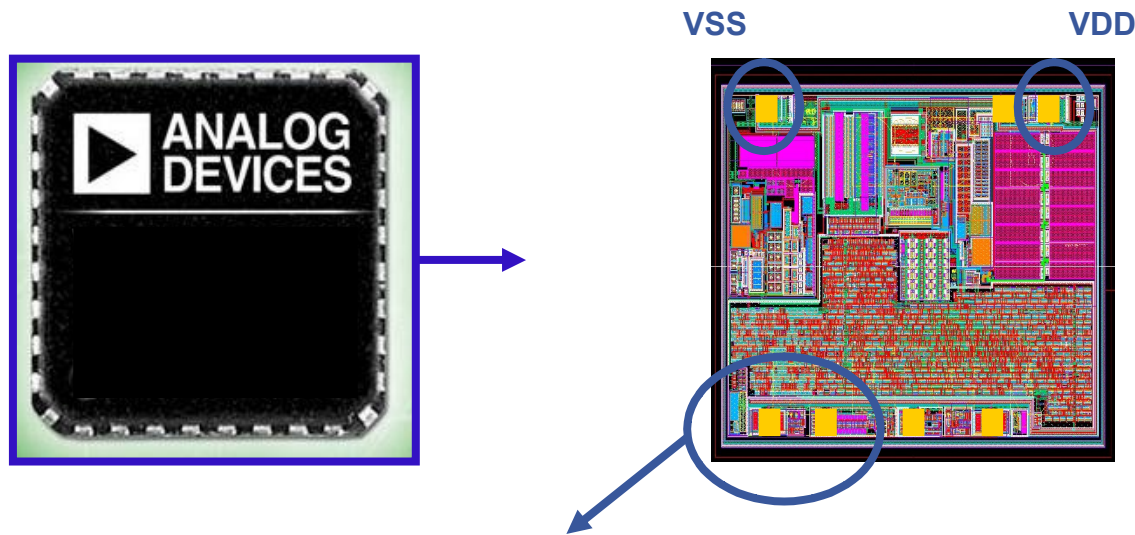
ESD DAMAGE in ICs (2)

Junction Damage/Contact Spiking



- SEM micrograph depicts NMOS after de-processing.

On-Chip ESD PROTECTION SCHEMES

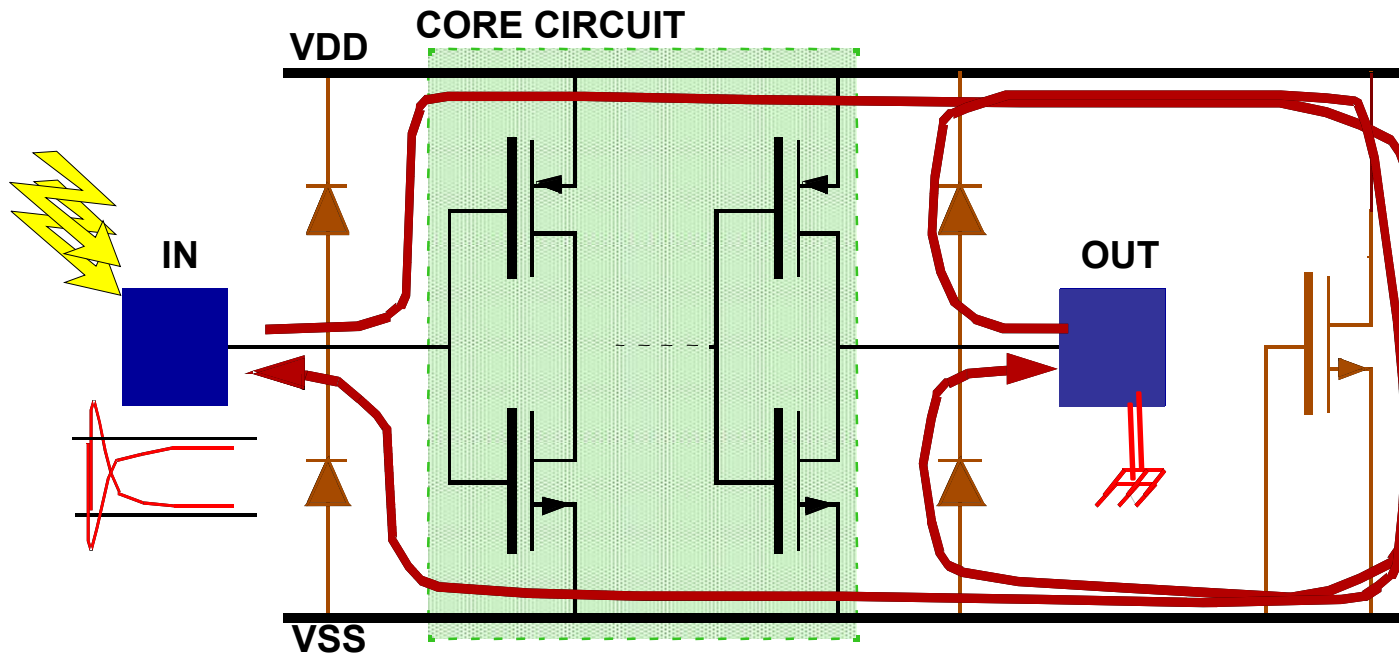


OBJECTIVE:

1. Shunt current discharges away from the *CORE CIRCUIT*
2. Clamps I/O & Power pad voltage to a safe level

On-Chip ESD PROTECTION SCHEMES

An Example





Circuit Simulation Considerations

- Impact of ESD structure on I/O and core circuits.
- ESD current paths.
- Impact of internal circuitry on ESD protection performance.
- Optimization to reduce ESD over design.



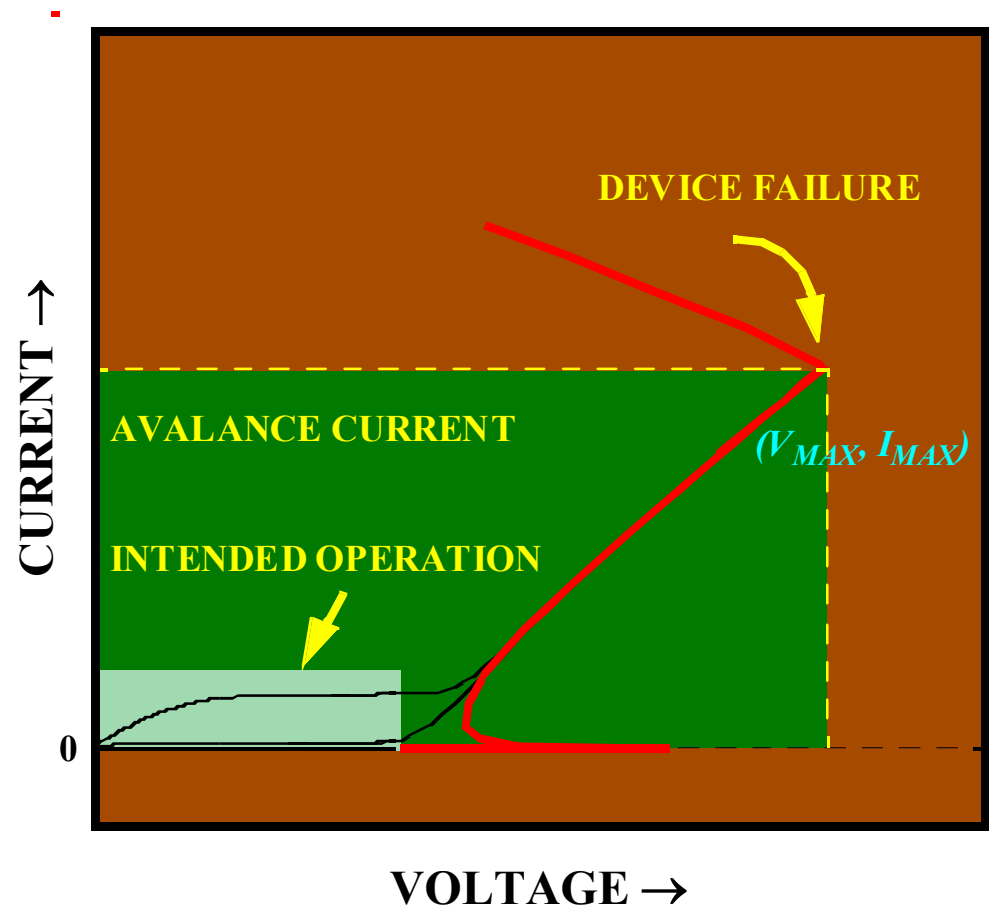
Circuit Simulation Approach

- ◆ **SPICE is a Primary Tool for Circuit Level Simulation**
- ◆ **ESD-capable Compact Device model**
- ◆ **Modeling physical phenomenon particular to ESD:**
 - *Breakdown*
 - *Snapback*
 - ...

Major Challenges (1)

- ◆ Devices operate in unintended bias space:
 - high voltages
 - very large currents

MOSFET CHARACTERISTICS

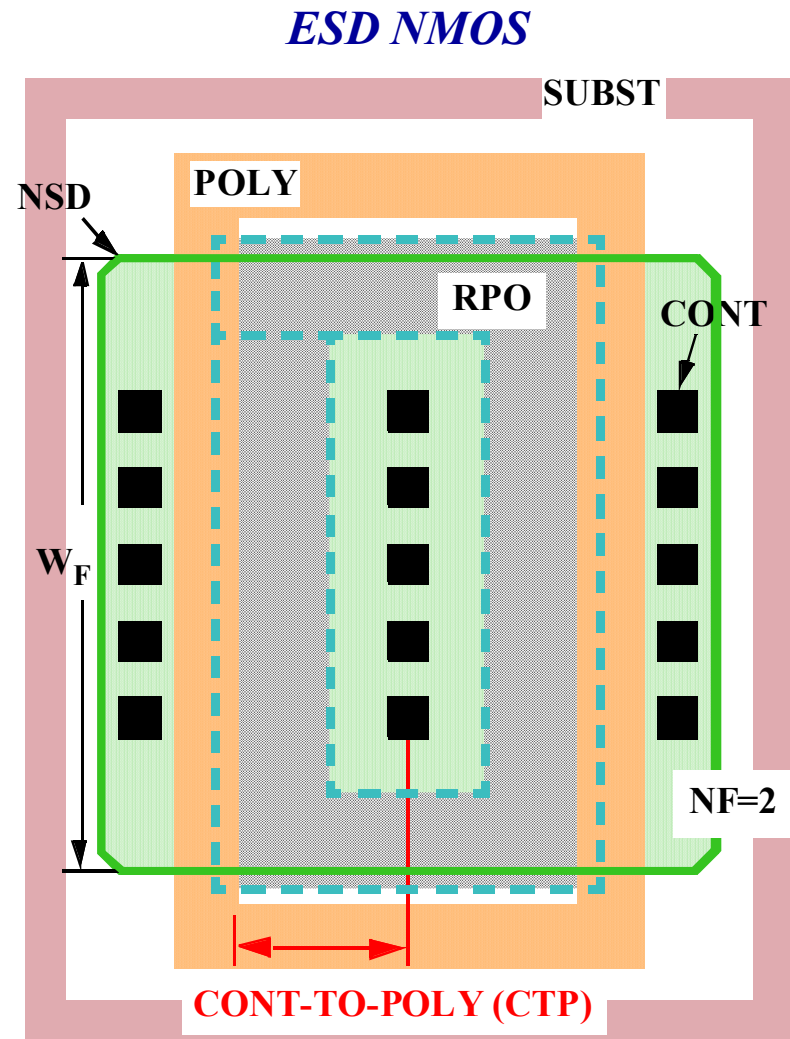


Major Challenges (2)

- ◆ Device operation highly dependent on layout.

- ESD NMOS – DESIGN SPACE

- ◆ Width
- ◆ Gate length
- ◆ w/ or w/o RPO in drain
- ◆ Drain side CTP
- ◆ Gate stripes
- ◆ Substrate contact





Major Challenges (3)

- ◆ Thermal effects important
- ◆ Parasitics (L , C & R) critical due to fast-transient nature of ESD:
 - Interconnect
 - Package
 - Board
 - Test fixture
 - ...



What Devices to Model?

Primary Protection Devices

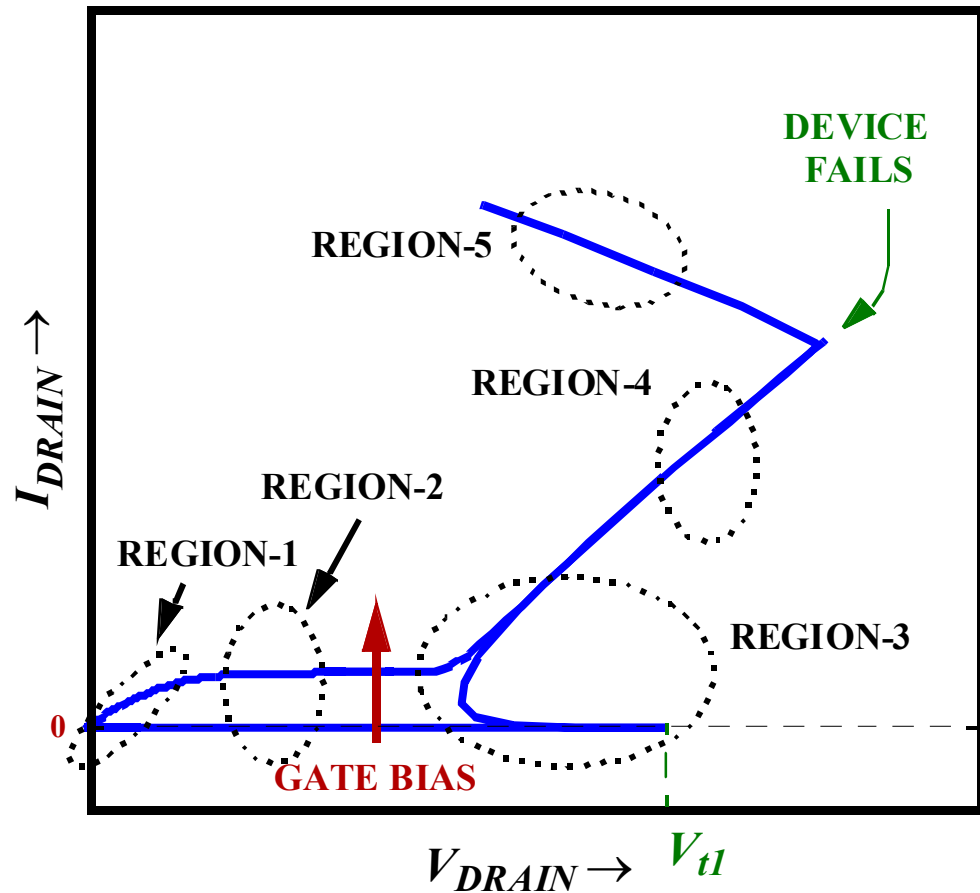
- 1) **MOS**
- 2) **SCR**
- 3) **Bipolar**
- 4) **Diodes**
- 5) **Resistors**

Modeling Strategy

- 1) **Modify standard Compact models**
- 2) **Customized Model**

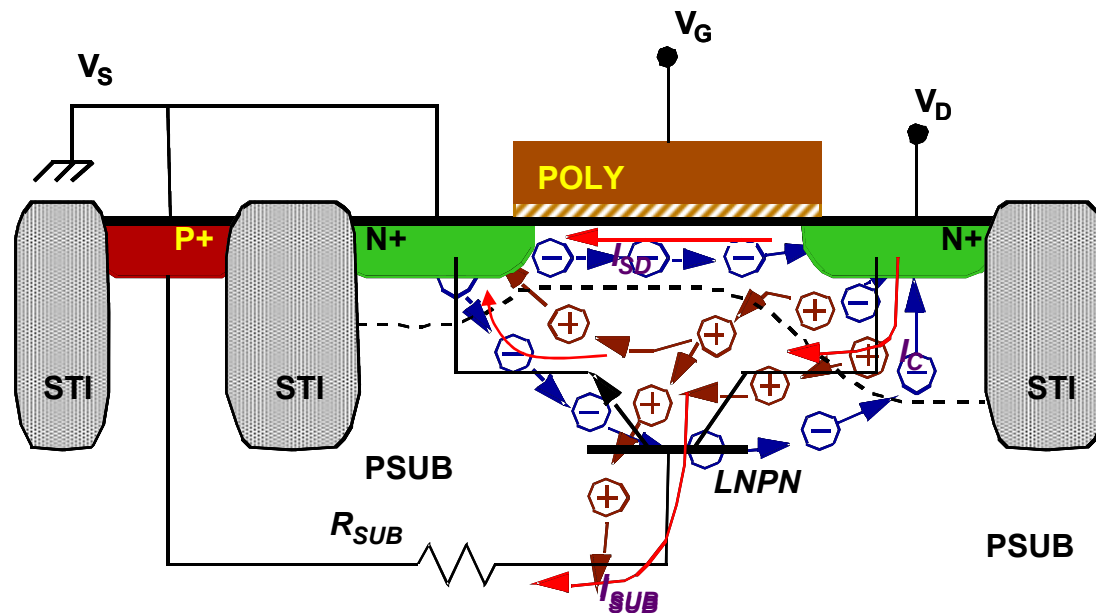
Snapback in ESD Devices

- ◆ Devices (MOS) operating in “snapback” mode carries more current per unit width
- ◆ Operating I-V Regions of MOS Devices
 - 1) Linear Region
 - 2) Saturation Region
 - 3) Avalanche Region
 - 4) Snapback Region
 - 5) Failure Region
- ◆ V_{t1} represents the “snapback effect” trigger voltage



Snapback in MOS Devices

Snapback Effect in MOS is due to the Parasitic BJT, triggered by the substrate current (I_{SUB}).



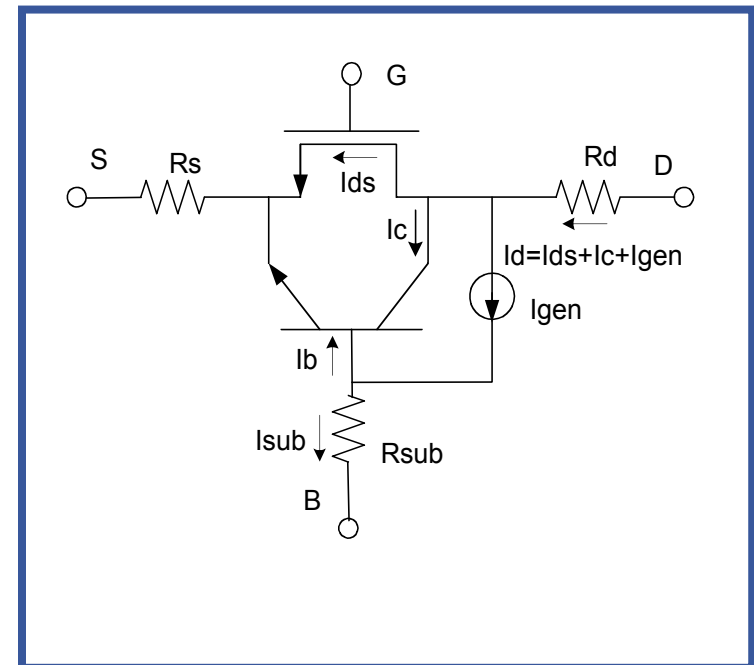


Critical Effects in Snapback Modeling

- ◆ **Substrate current as function of V_{DS} , V_{GS} and V_{BS}**
 - **Due to impact ionization in Drain/Backgate depletion layer.**
 - **Avalanche current multiplication factor is different before and after snapback**
 - **Displacement current (dV/dt) through Drain/Backgate junction**
 - **Gate induced drain leakage (GIDL)**

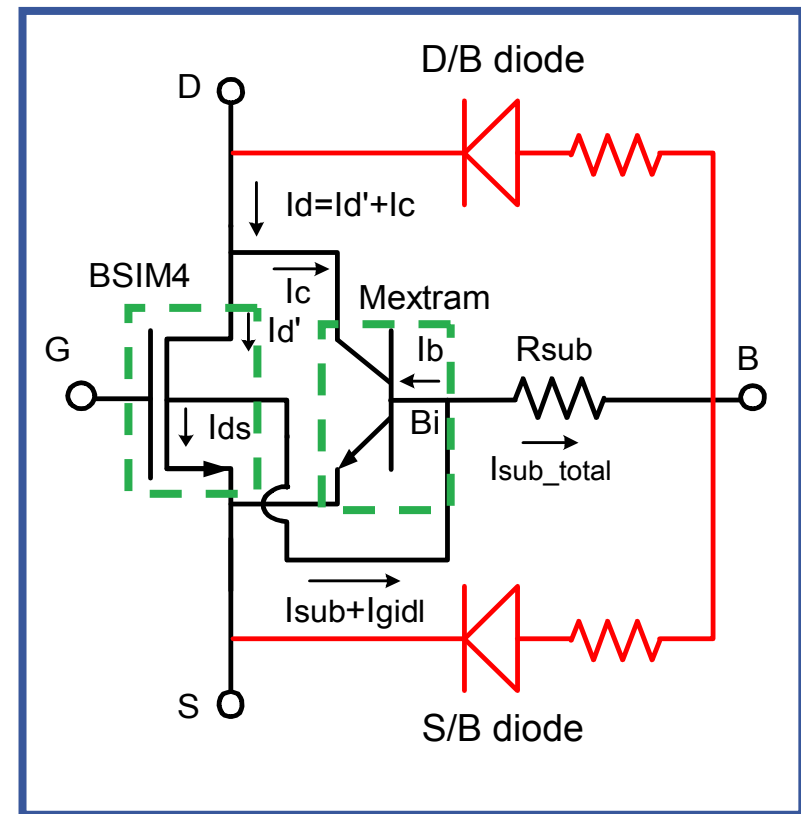
Previous Snapback Models

- ◆ Standard MOS and BJT models.
- ◆ An explicit current source which is a function of V_{GS} and V_{DS}
- ◆ (dV/dt) effect, GIDL and separate M for MOS and BJT are included in some models by adding equations.
- ◆ The implementation of the models includes C code and behavioral languages (*Verilog-A*)



Model for MOS under ESD Stress

- ◆ New approach eliminates the current source of previous models.
- ◆ Model constructed of standard BJT (Mextram) and MOS (BSIM4) devices.
- ◆ Models intrinsically includes all major physical phenomenon presented.
- ◆ Source/Backgate and Drain/Backgate Junction Diodes for completeness.

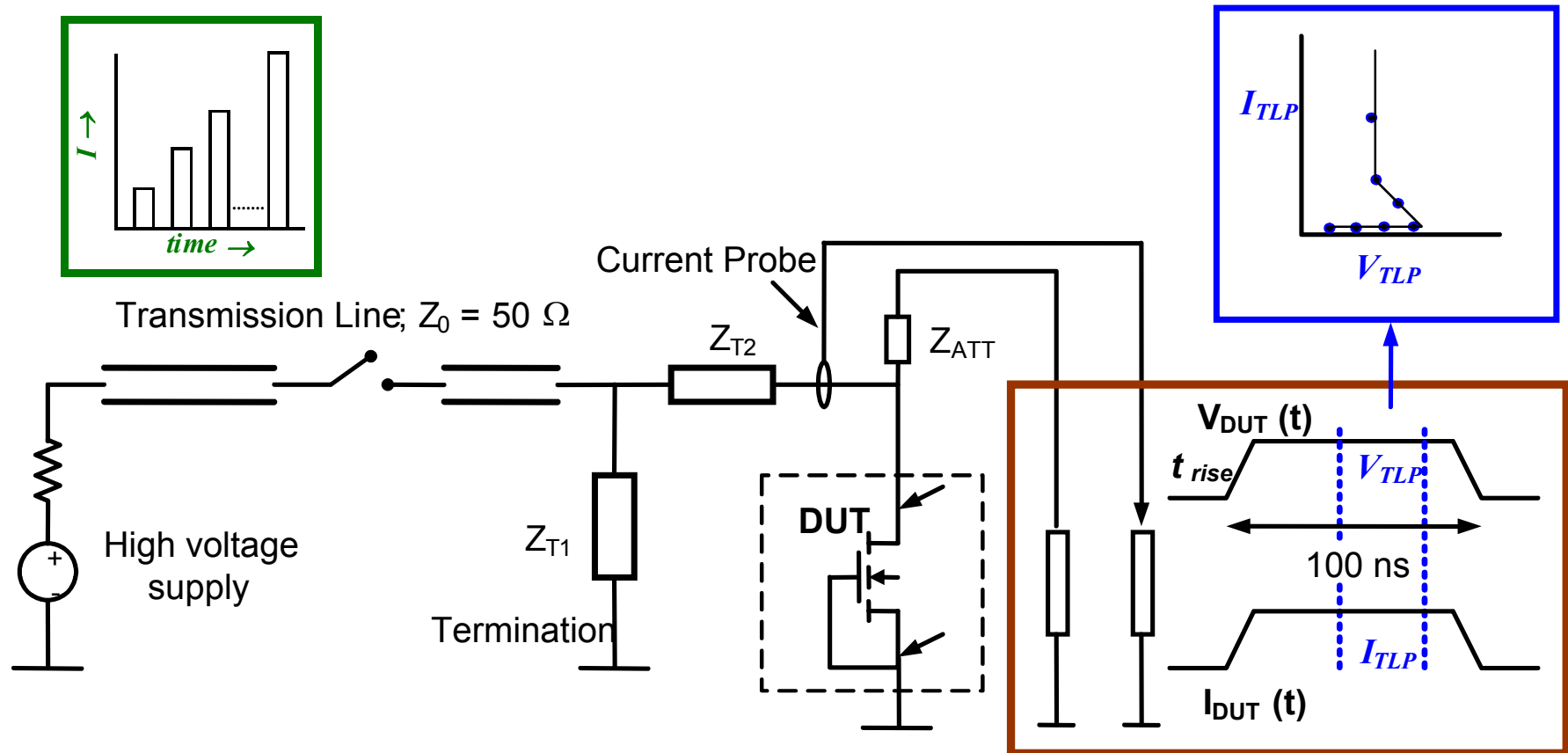




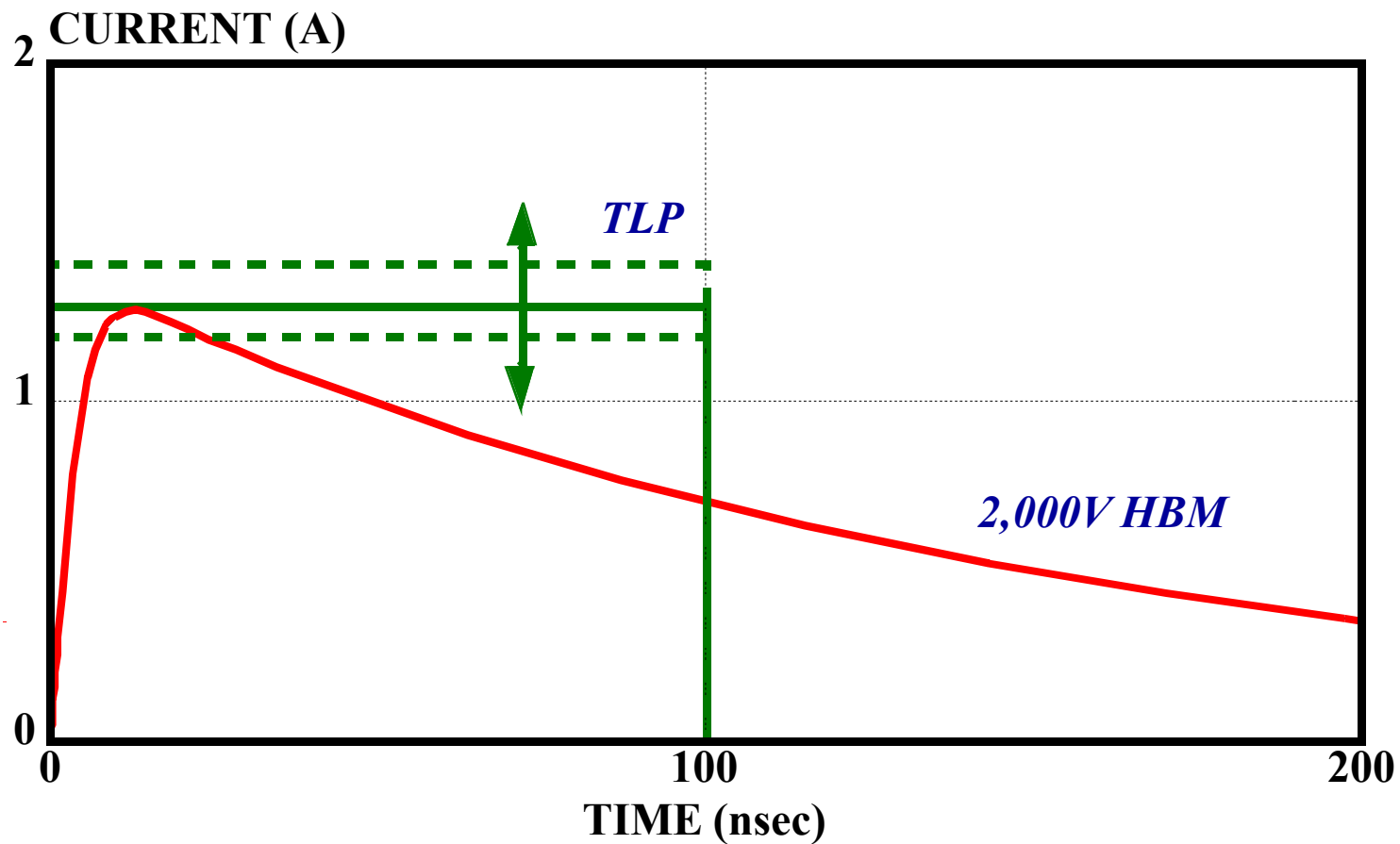
Model Verification

- ◆ **Transmission Line Pulse measurement:**
 - *Quasi-static*
 - *Transient*

Transmission Line Pulse (TLP) Measurement Setup

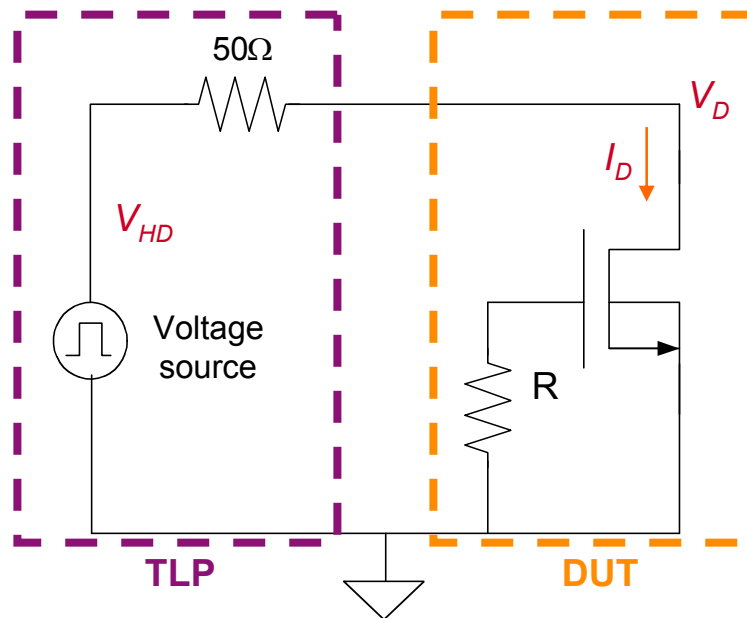


Why Transmission Line Pulse?



Model Verification

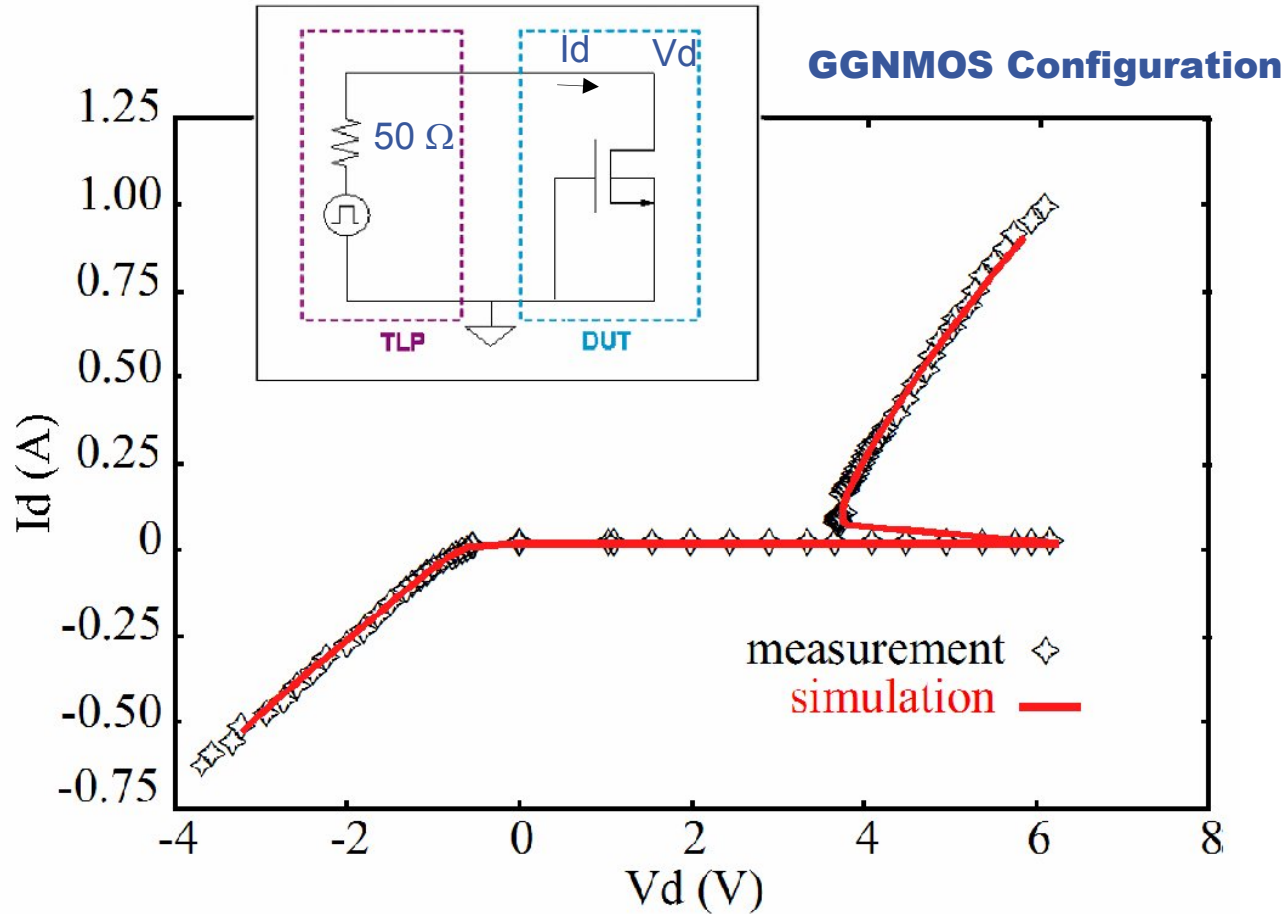
- ◆ Snapback effect was simulated with transient simulation.
- ◆ Voltage Pulse Sequence (100ns) were used as the Input.
- ◆ The stabilized V_D and I_D were measured as the simulation results (~80ns).



Schematic of
Snapback Simulation
($R=0\Omega$ for ggNMOS)

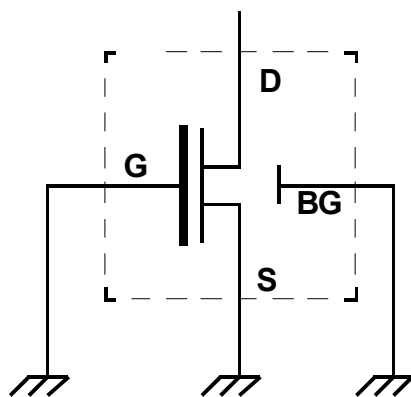
Simulation Results vs. TLP Measurement

A ggNMOS device

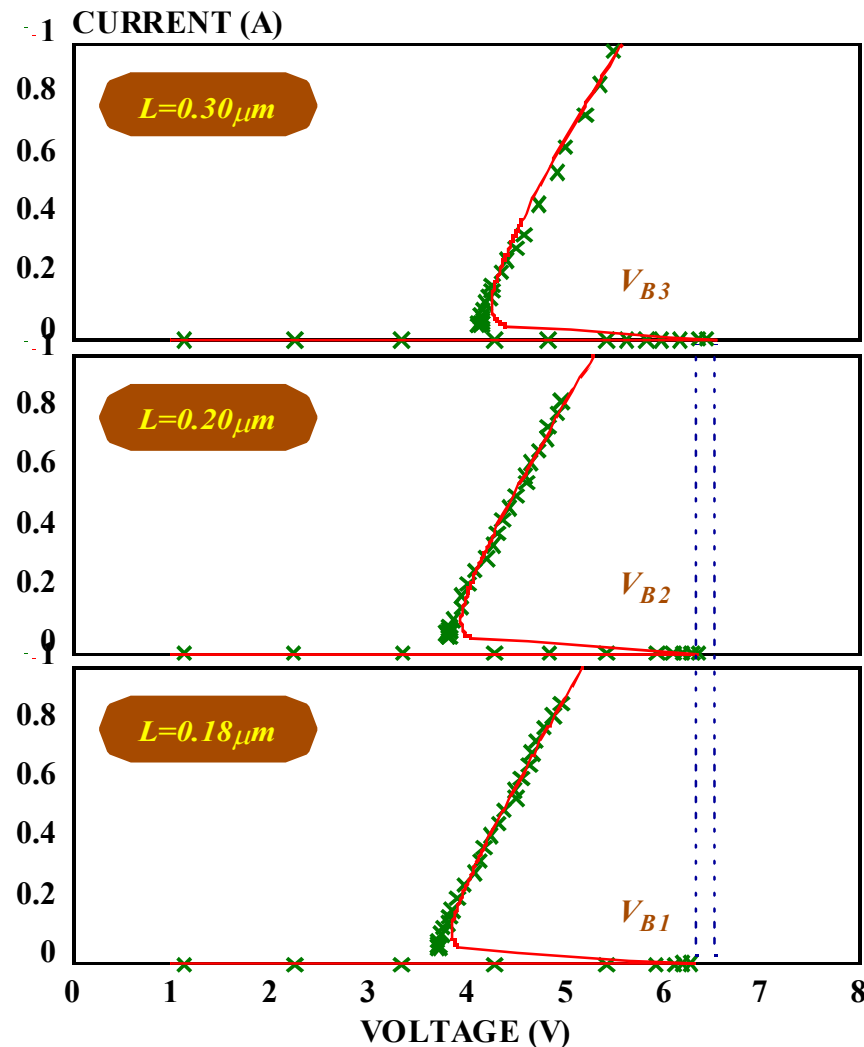


MOS CHARACTERISTICS & MODEL

- ◆ Deep submicron CMOS
- ◆ Model Scalability
 - ◆ $W = 300\mu\text{m}$
 - ◆ $0.18 < L < 0.30 \mu\text{m}$
 - ◆ Stripes = 12
 - ◆ Wrap-around backgate contact

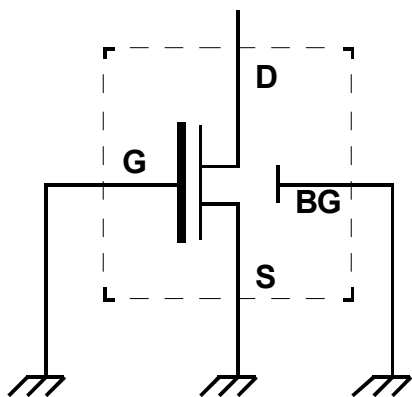


GGNMOS

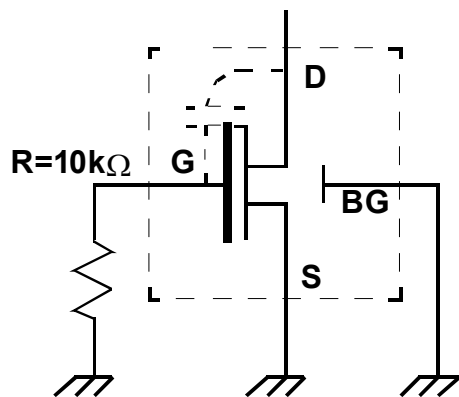


MOS CHARACTERISTICS & MODEL

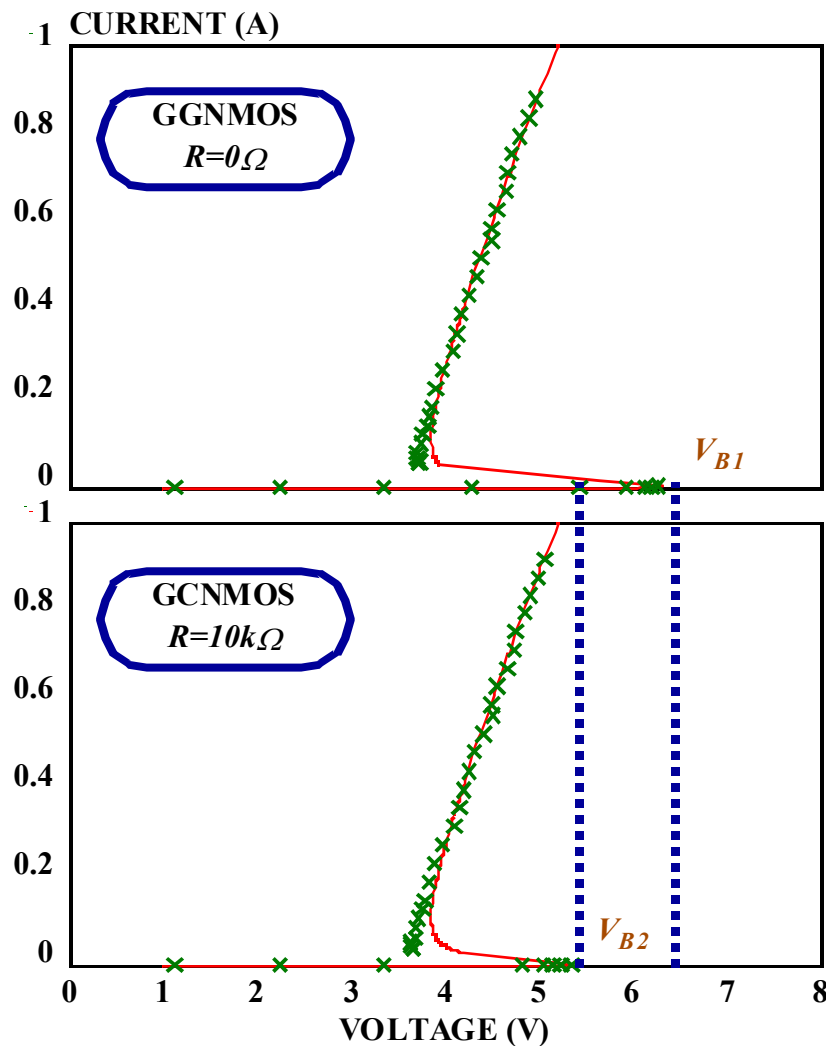
- ◆ Deep submicron CMOS
 - ◆ W/L = 300/0.18 μ m; Stripes = 12



GGNMOS

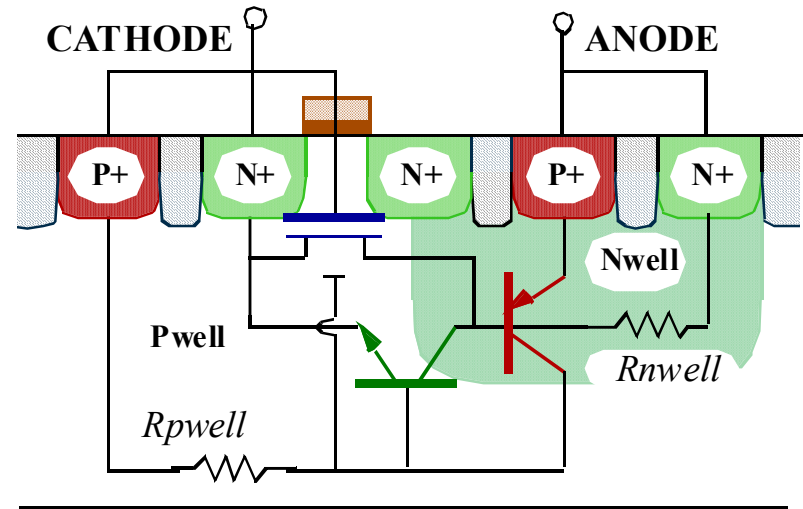
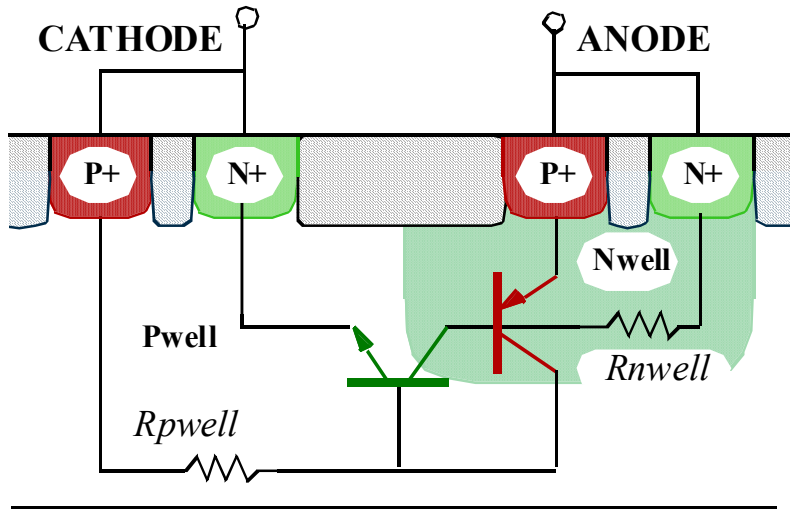


GCNMOS

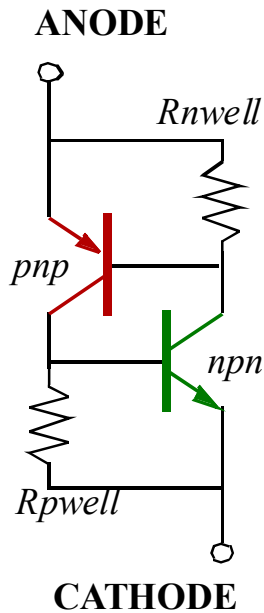


100ns TLP: Sim vs. msmt

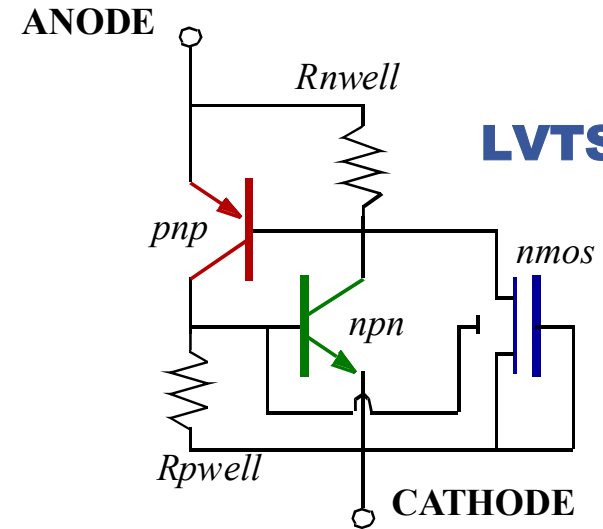
SCR Devices



SCR

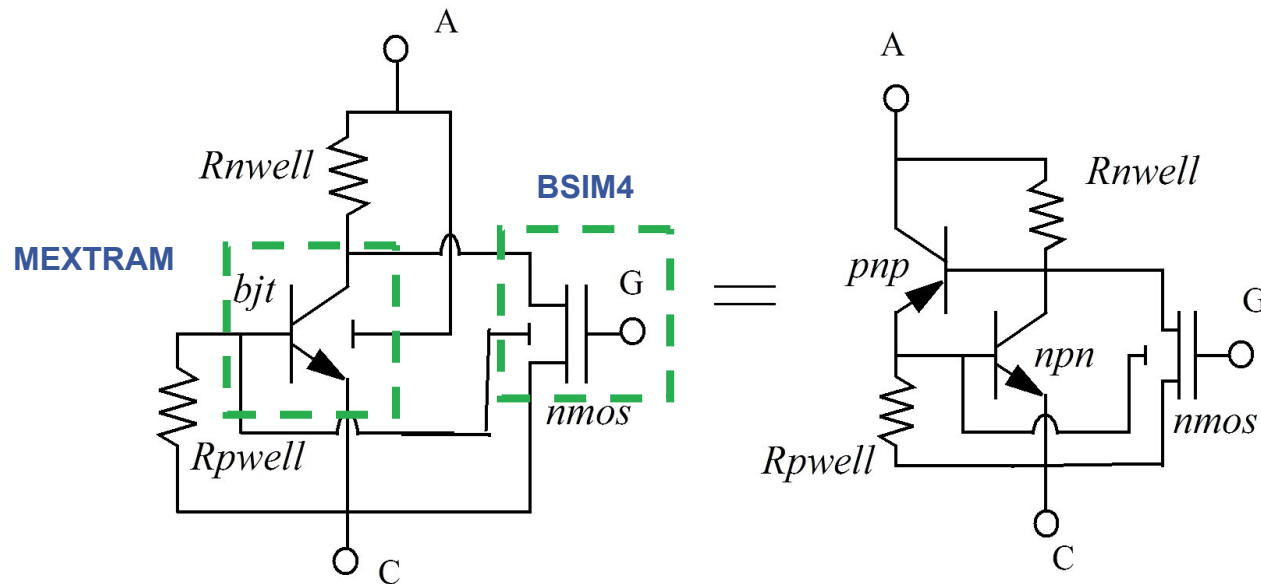


LVTSCR



Macro Model for LVTSCR

- ◆ Similar approach to MOS
- ◆ New model consists of four components:
 - An NMOS modeled by BSIM4
 - A four terminal NPN modeled by Mextram
 - Two resistors



Key effects in New LVTSCR Macro Model

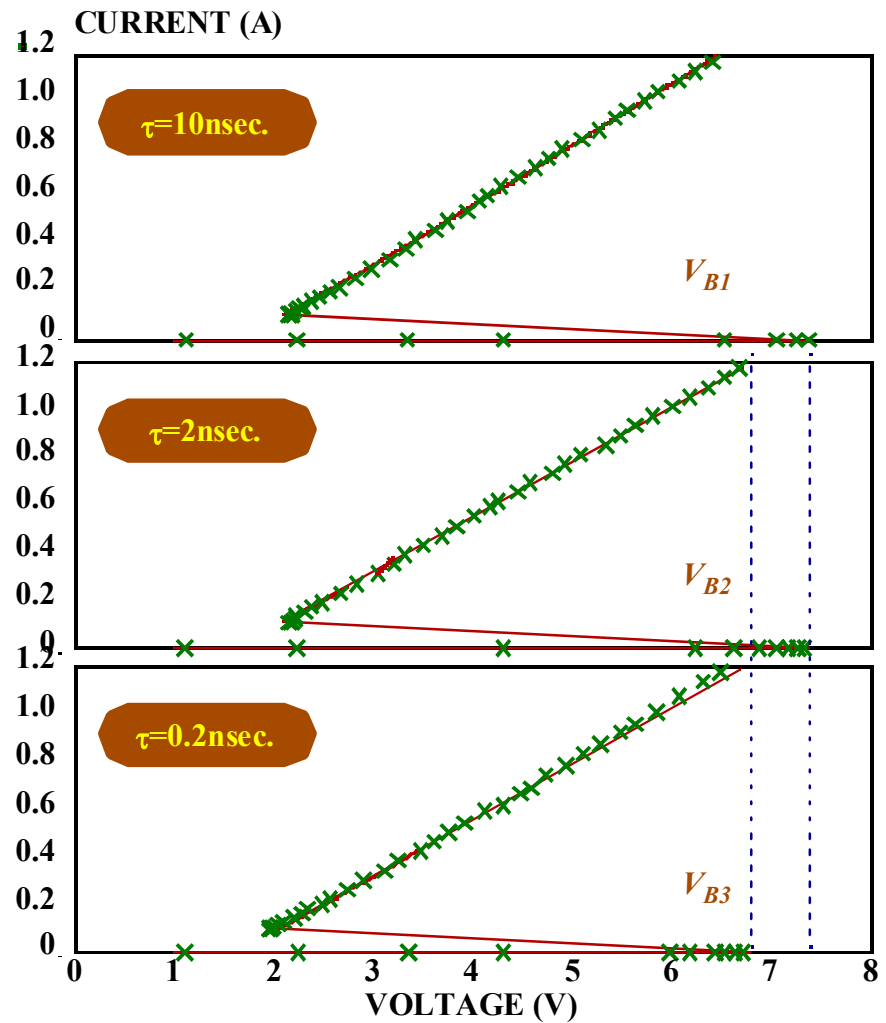
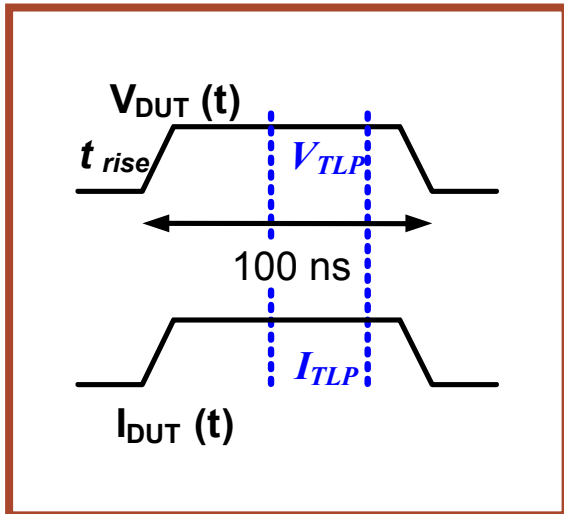
- ◆ The PNP is modeled by the parasitic BJT in the 4 terminal NPN modeled by a Mextram-like model
- ◆ Current sources for avalanche and GIDL are intrinsically built in MOS and BJT models

$$I_{GEN} = I_{AVL} + I_{SUB} + I_{GIDL}$$

- ◆ Decoupled multiplication factors for BJT and MOS are included in I_{AVL} and I_{SUB} respectively
- ◆ The dV/dt effect is modeled by Collector/Base junction capacitance of the BJT

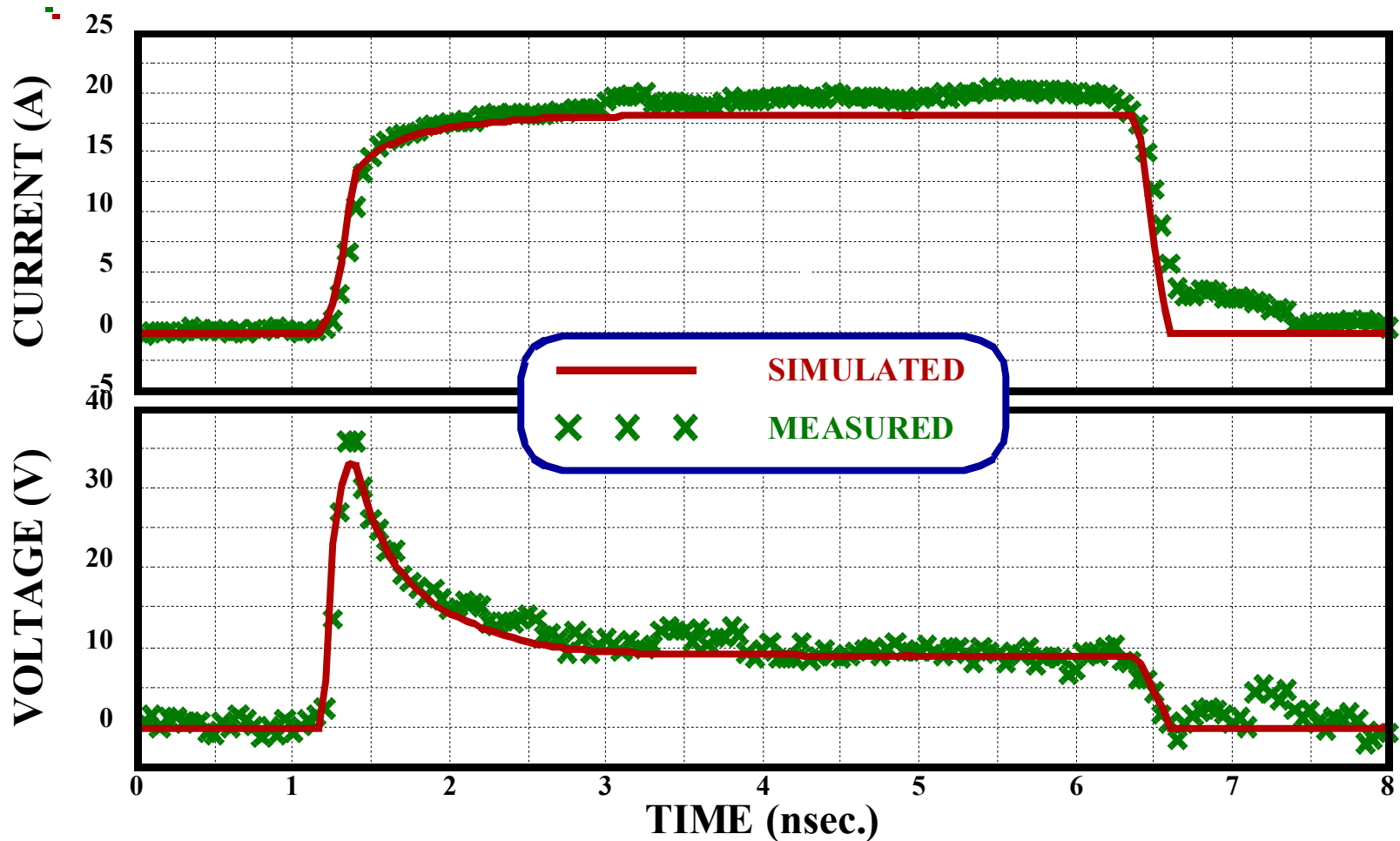
SCR CHARACTERISTICS & MODEL

- ◆ CMOS: **SCR-1**
- ◆ 100nsec TLP Pulse
 - Different pulse rise-time



SCR CHARACTERISTICS & MODEL

◆ CMOS: SCR-1



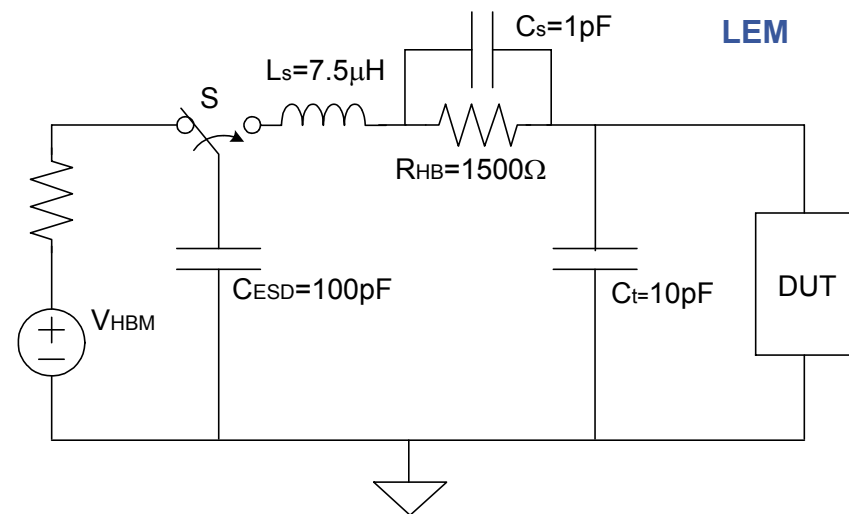
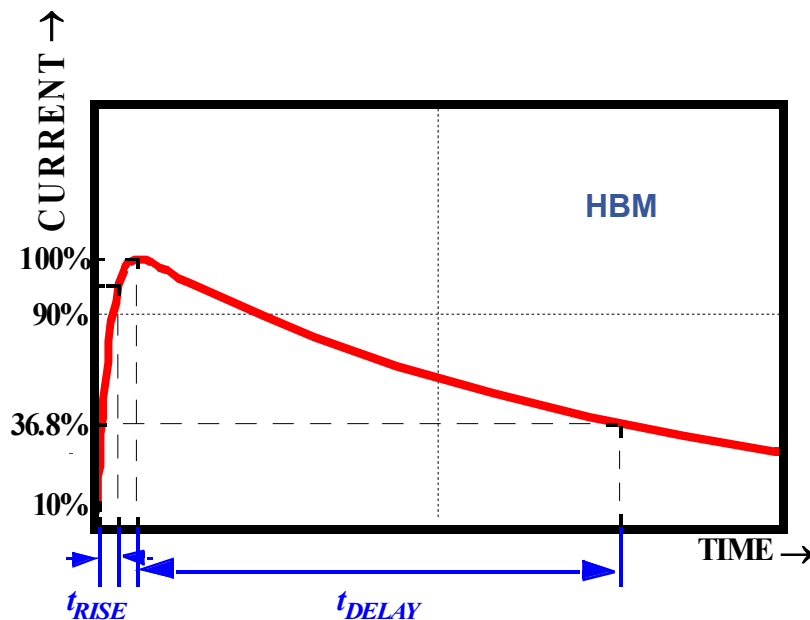
VFTLP: SCR ADICE Simulation vs. measurement

—Analog Devices Proprietary Information—

CIRCUIT SIMULATION

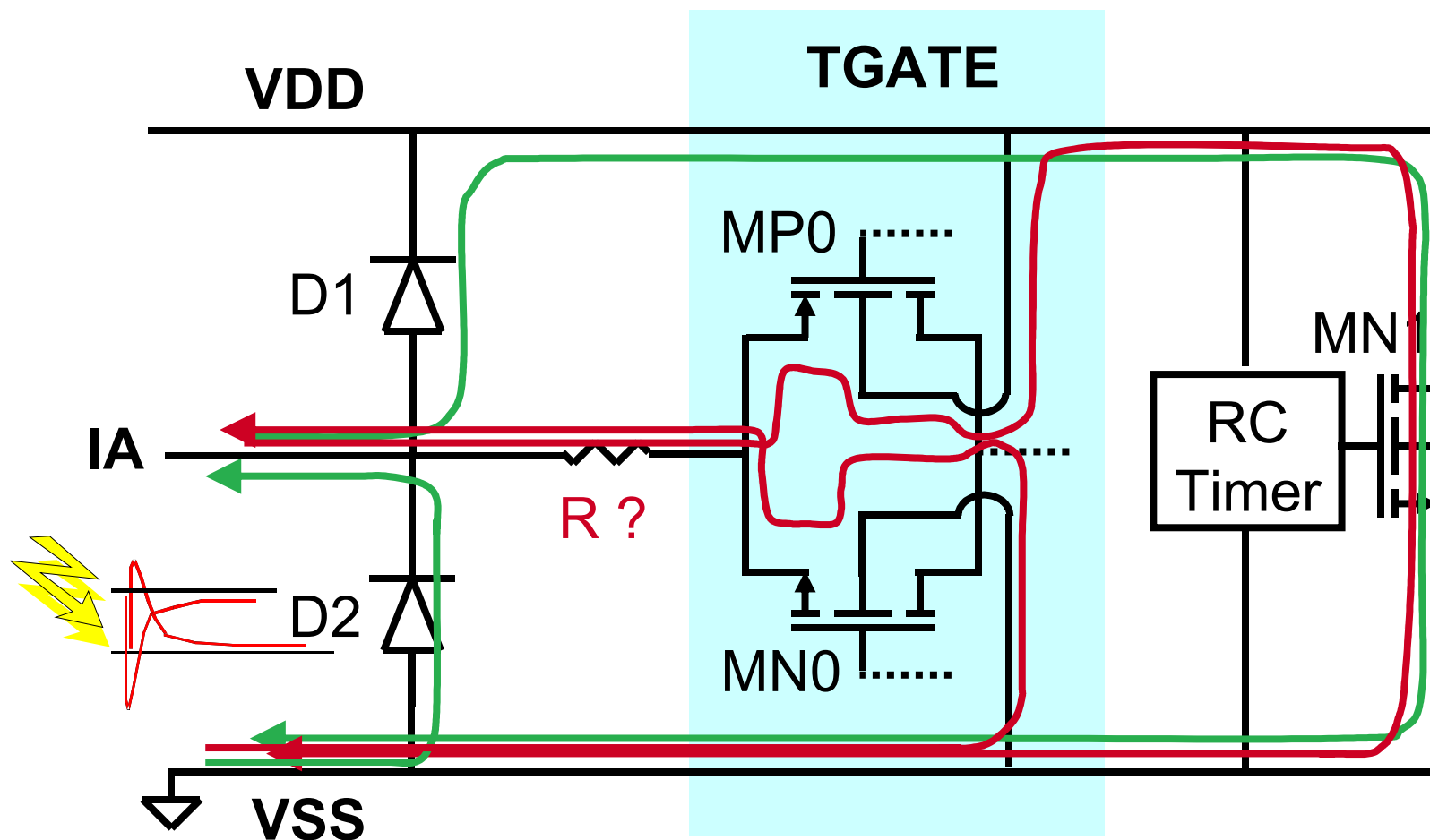
Human Body Model (HBM)

- ◆ Simulates the discharge from the finger of a standing person
- ◆ $I_{PEAK} = \sim 0.67 \text{ A/kV}$, $t_{RISE} \sim 5\text{-}9\text{ns}$, $t_{DELAY} = \sim 150 \text{ nsec}$.
- ◆ Modeled by a Lumped Element Model (LEM)



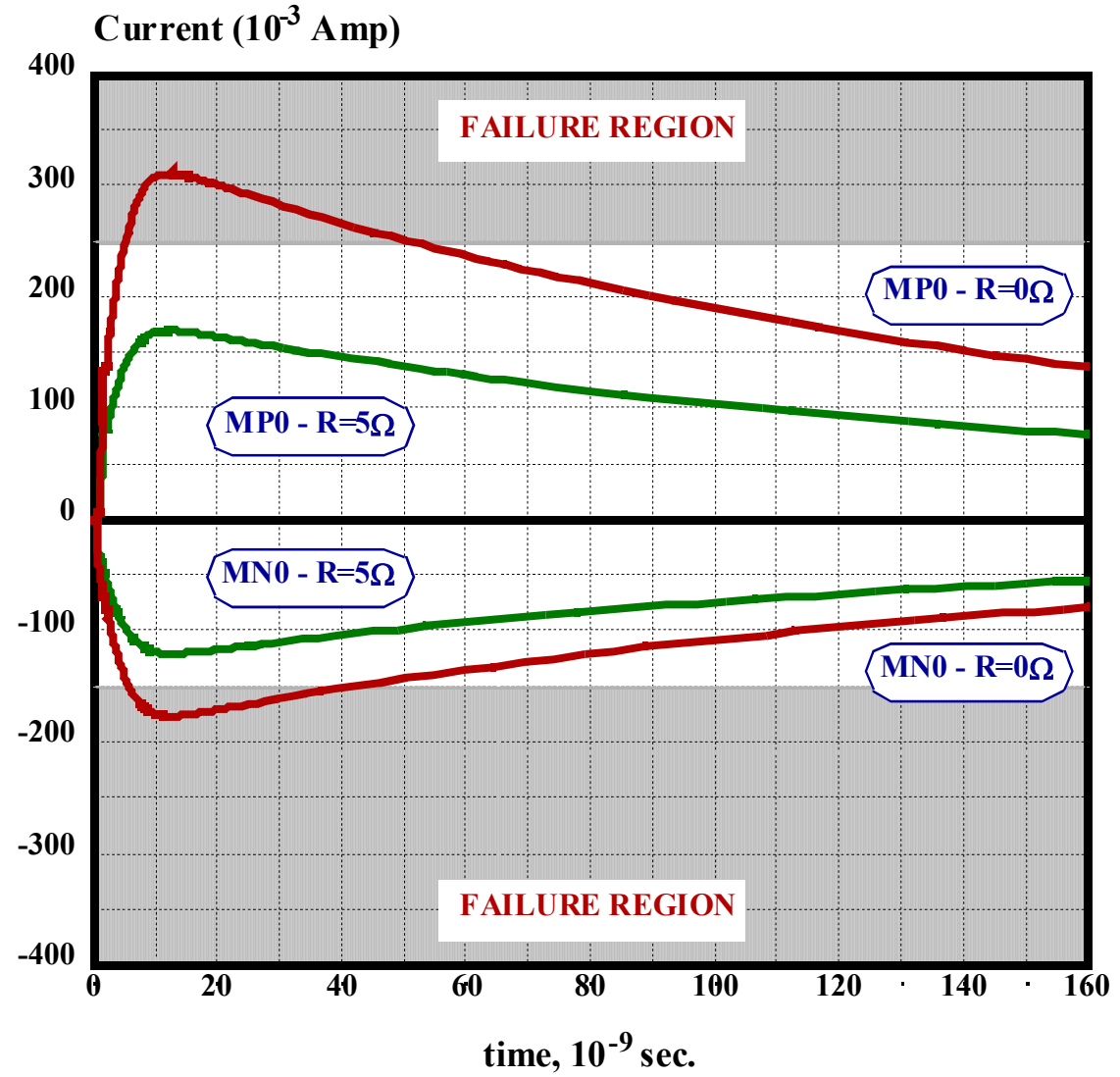
SPICE Simulation Examples

I/O Cell – Circuit



SPICE Simulation Examples

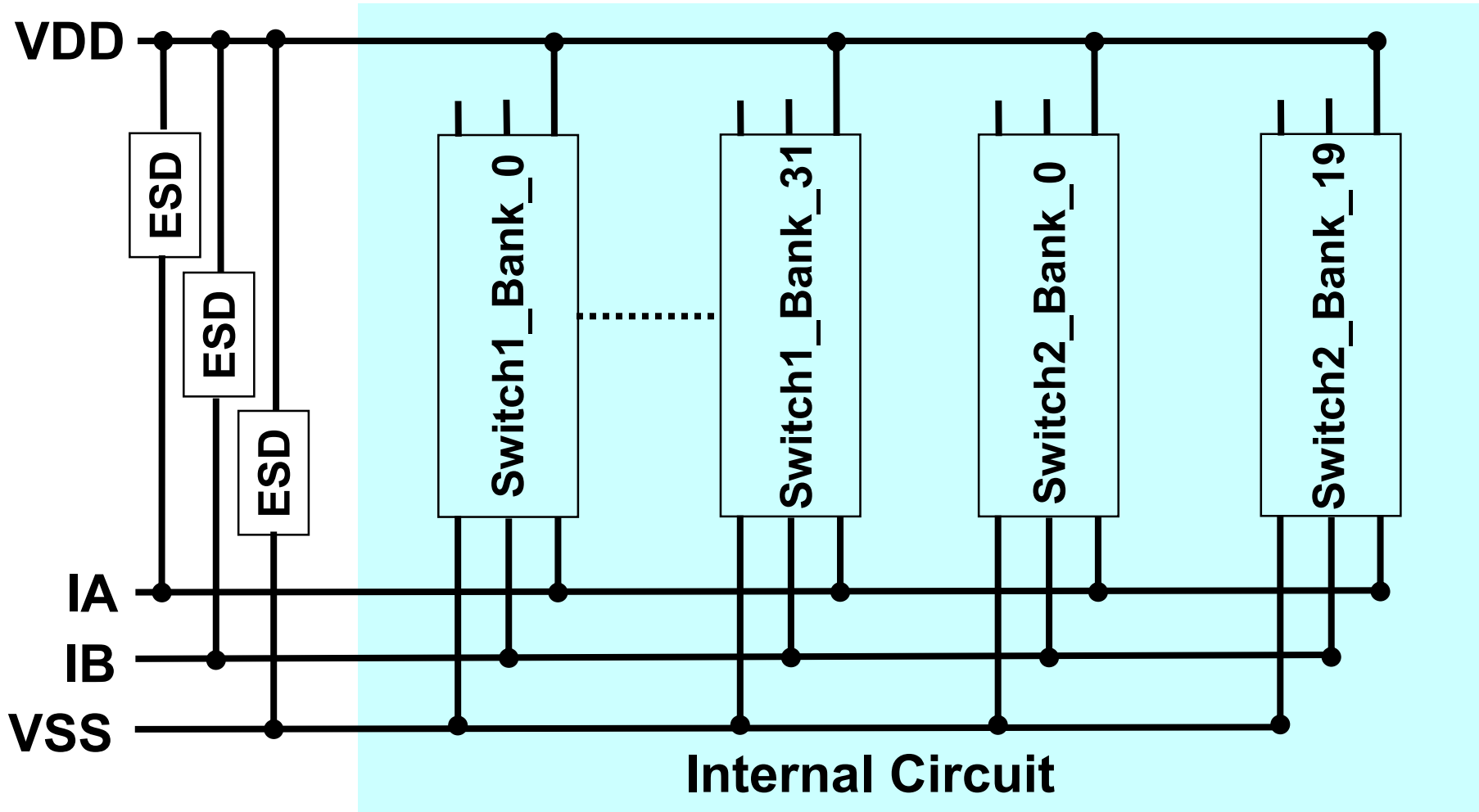
I/O Cell – Simulation



$W_{PMOS} \sim 2W_{NMOS}$

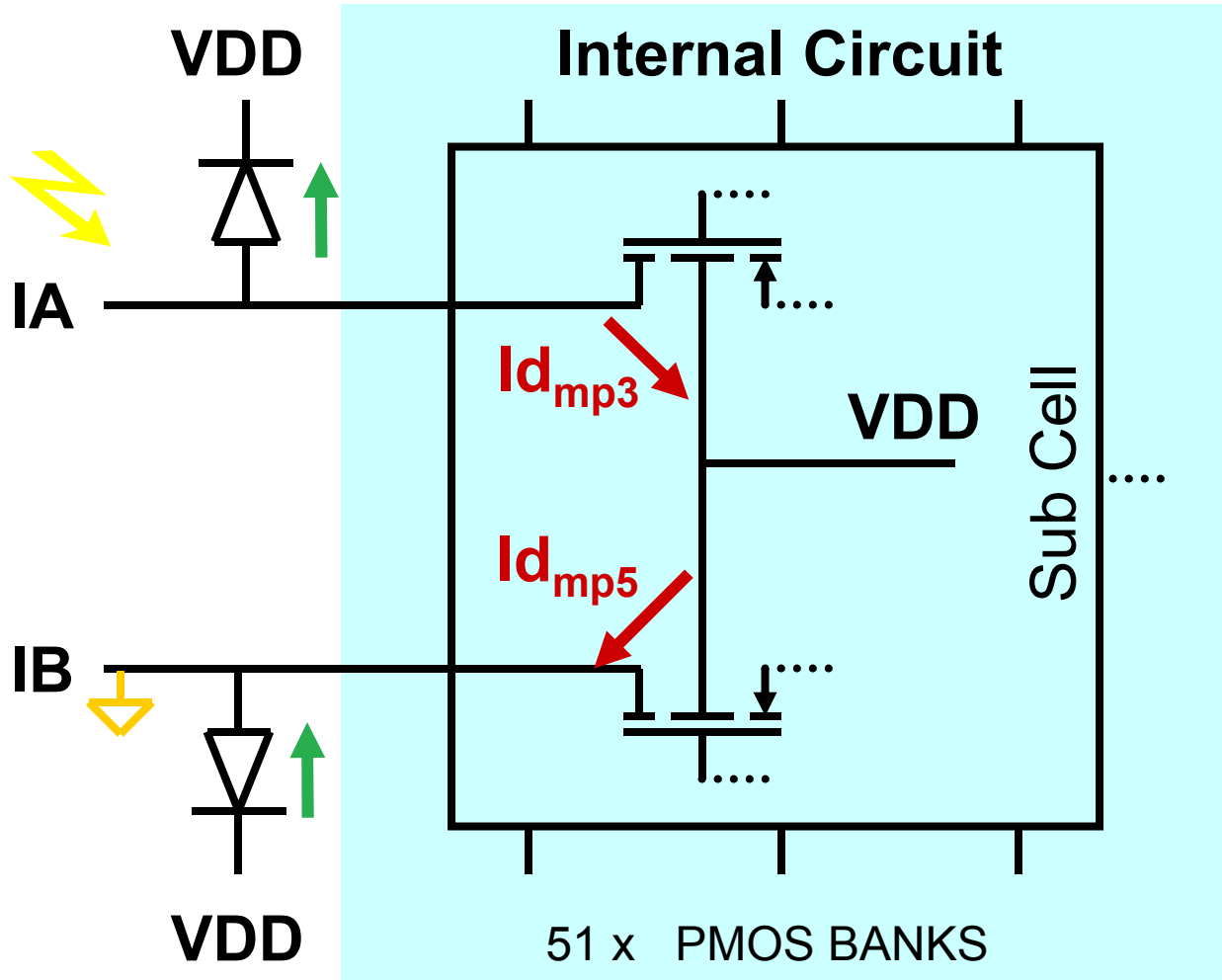
SPICE Simulation Examples

Block Level



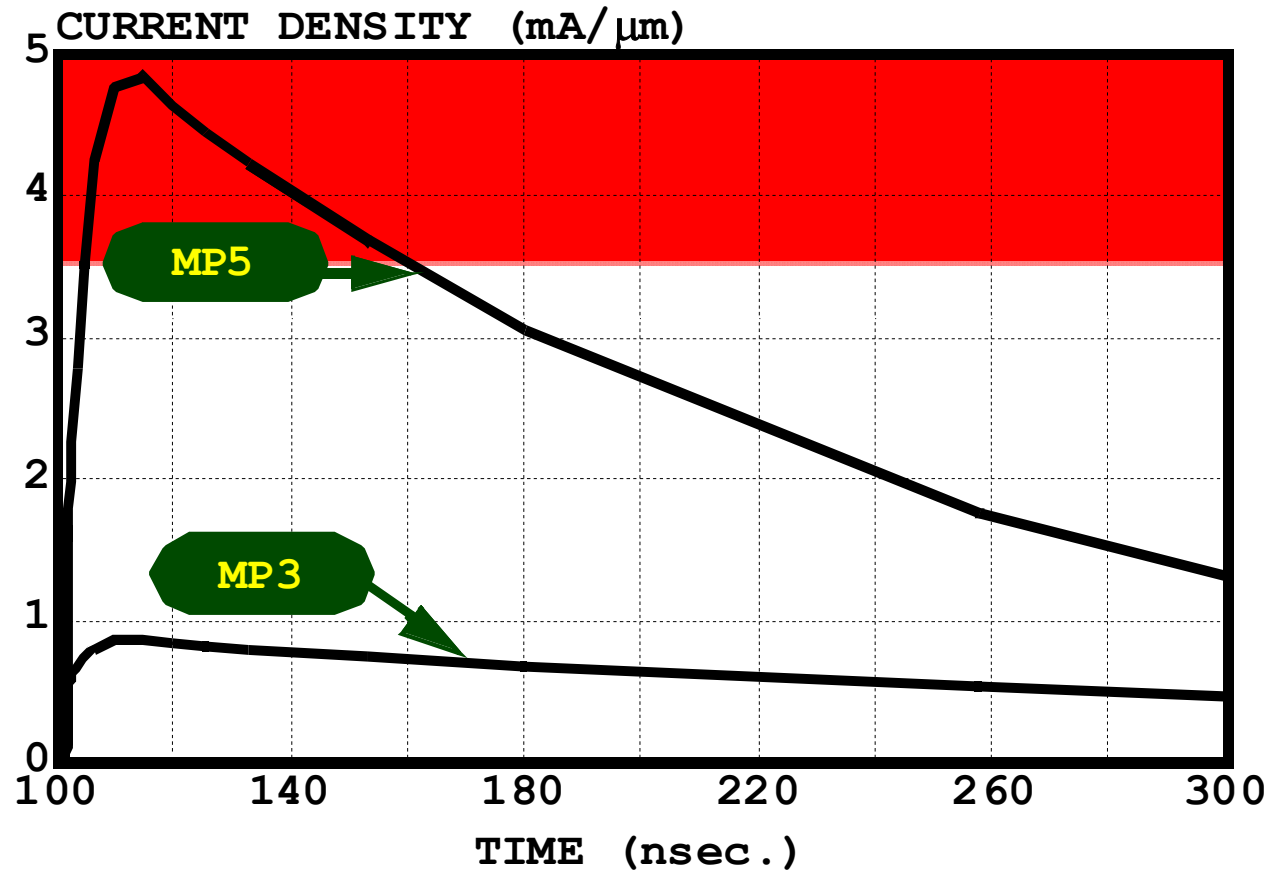
SPICE Simulation Examples

Block Level – Original Design Fails 1,000V HBM



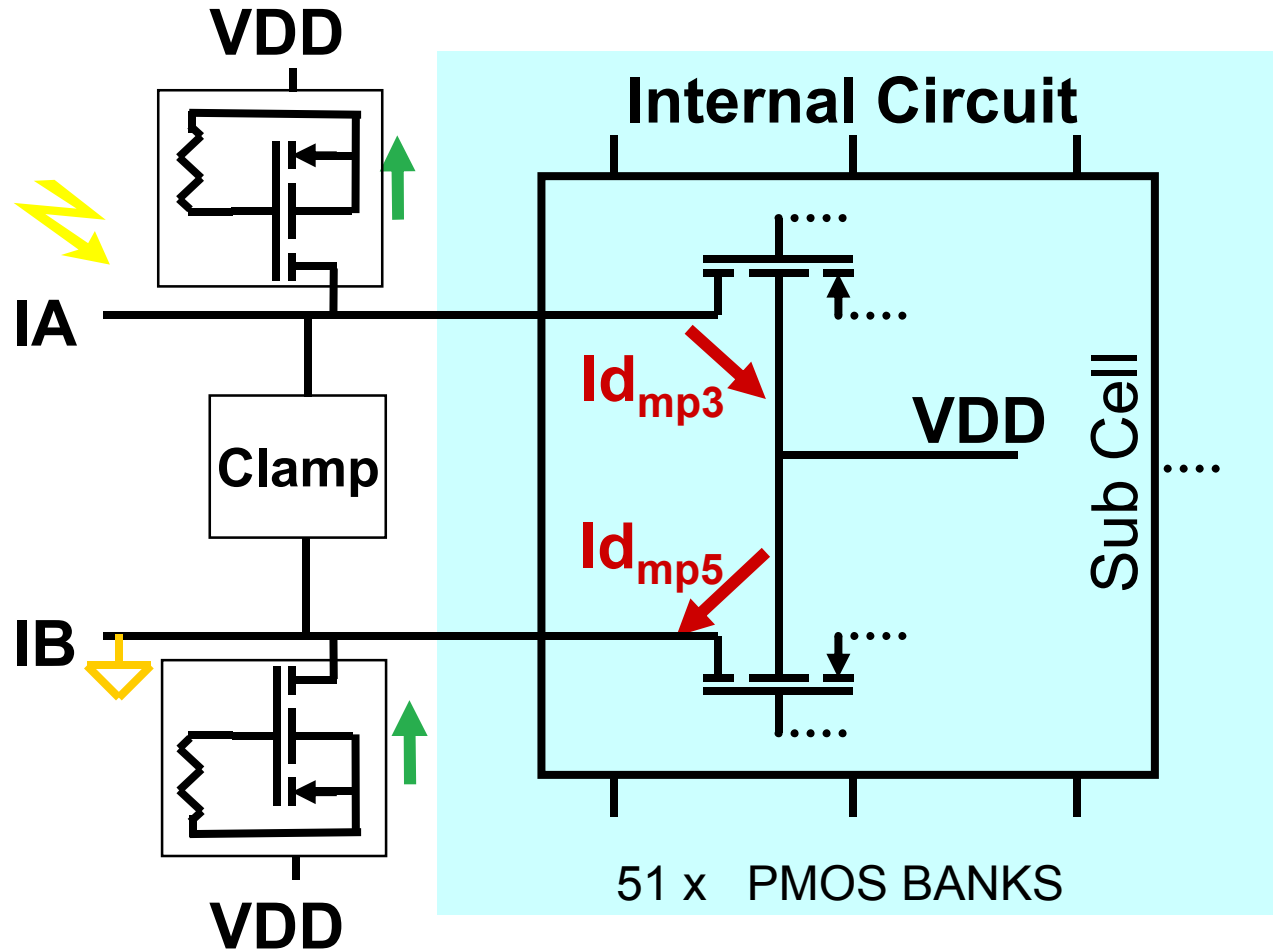
SPICE Simulation Examples

Block Level – Simulation Results – Fails 1,000V



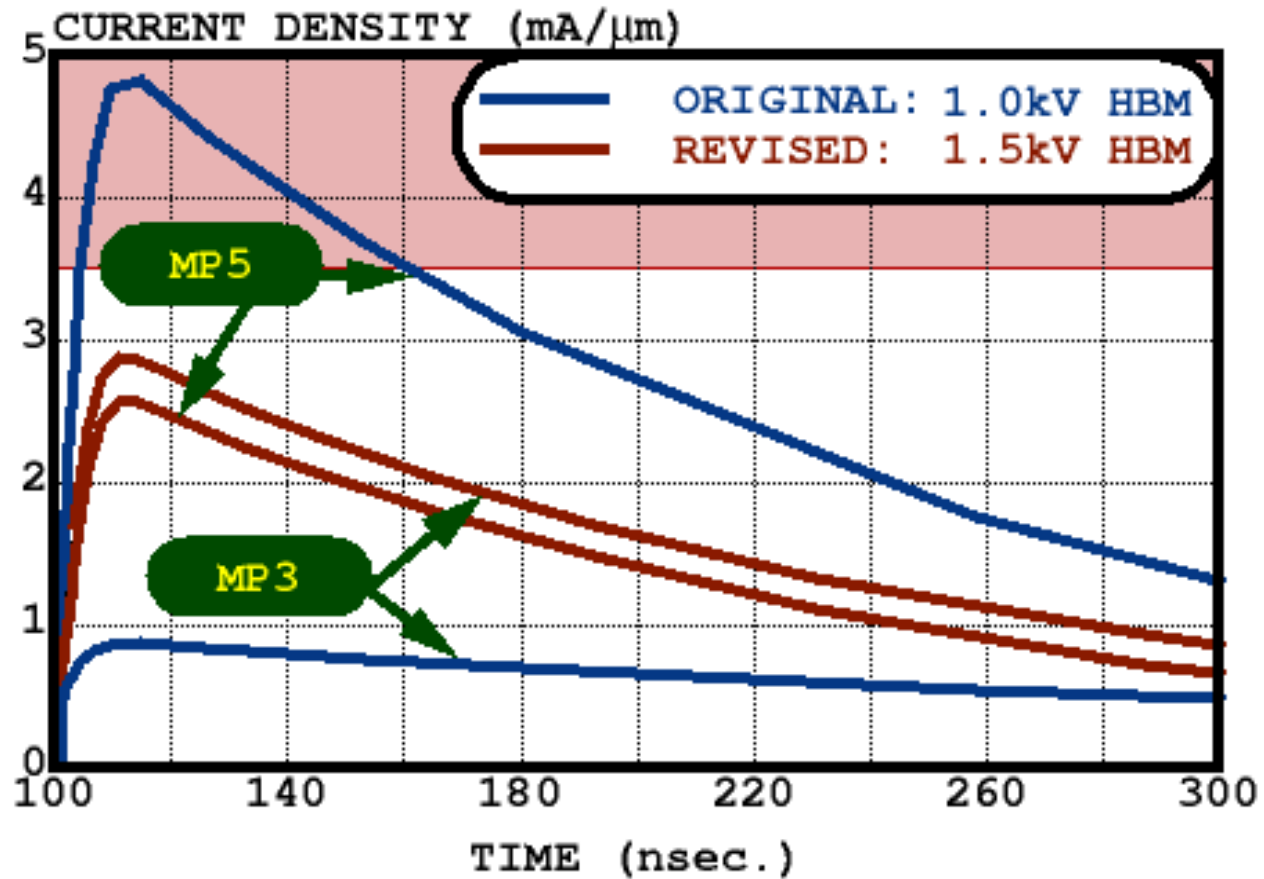
SPICE Simulation Examples

Block Level – Revised Design Passes 1,500V HBM



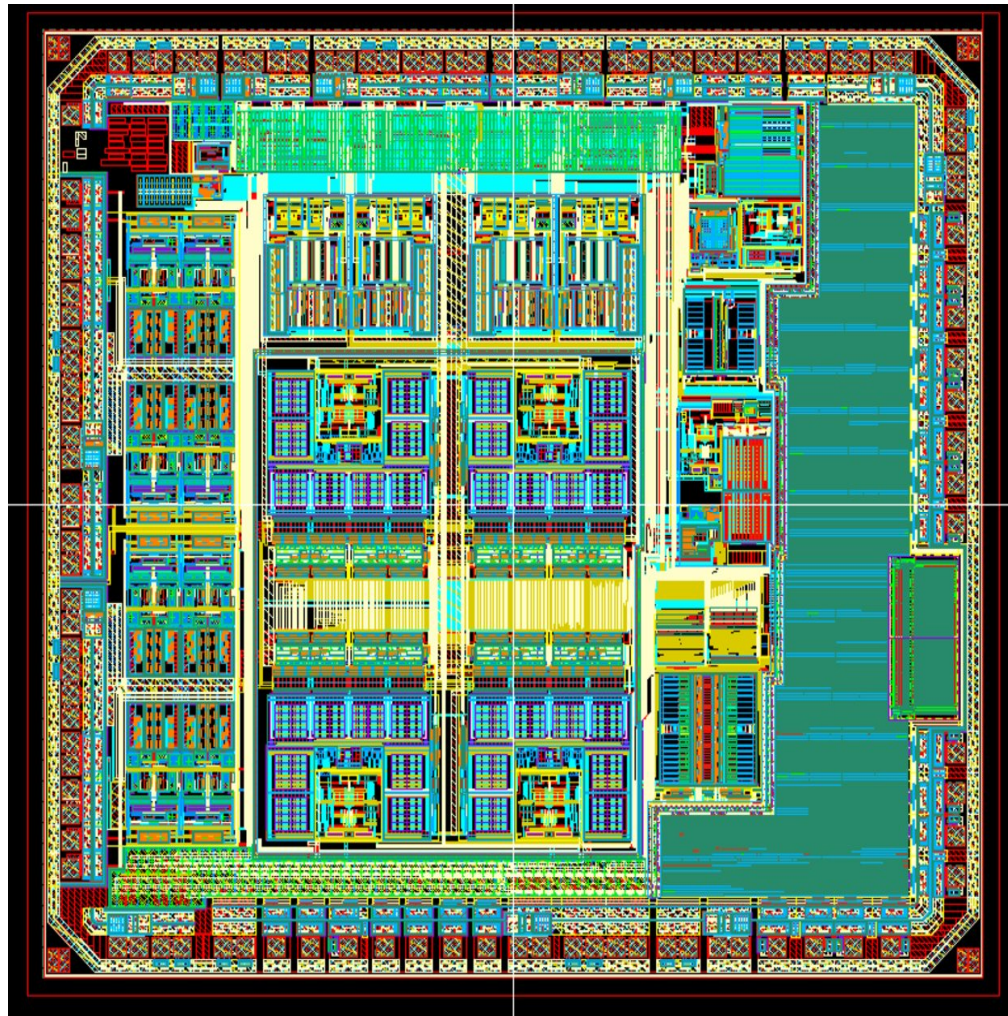
SPICE Simulation Examples

Block Level – Simulation Results



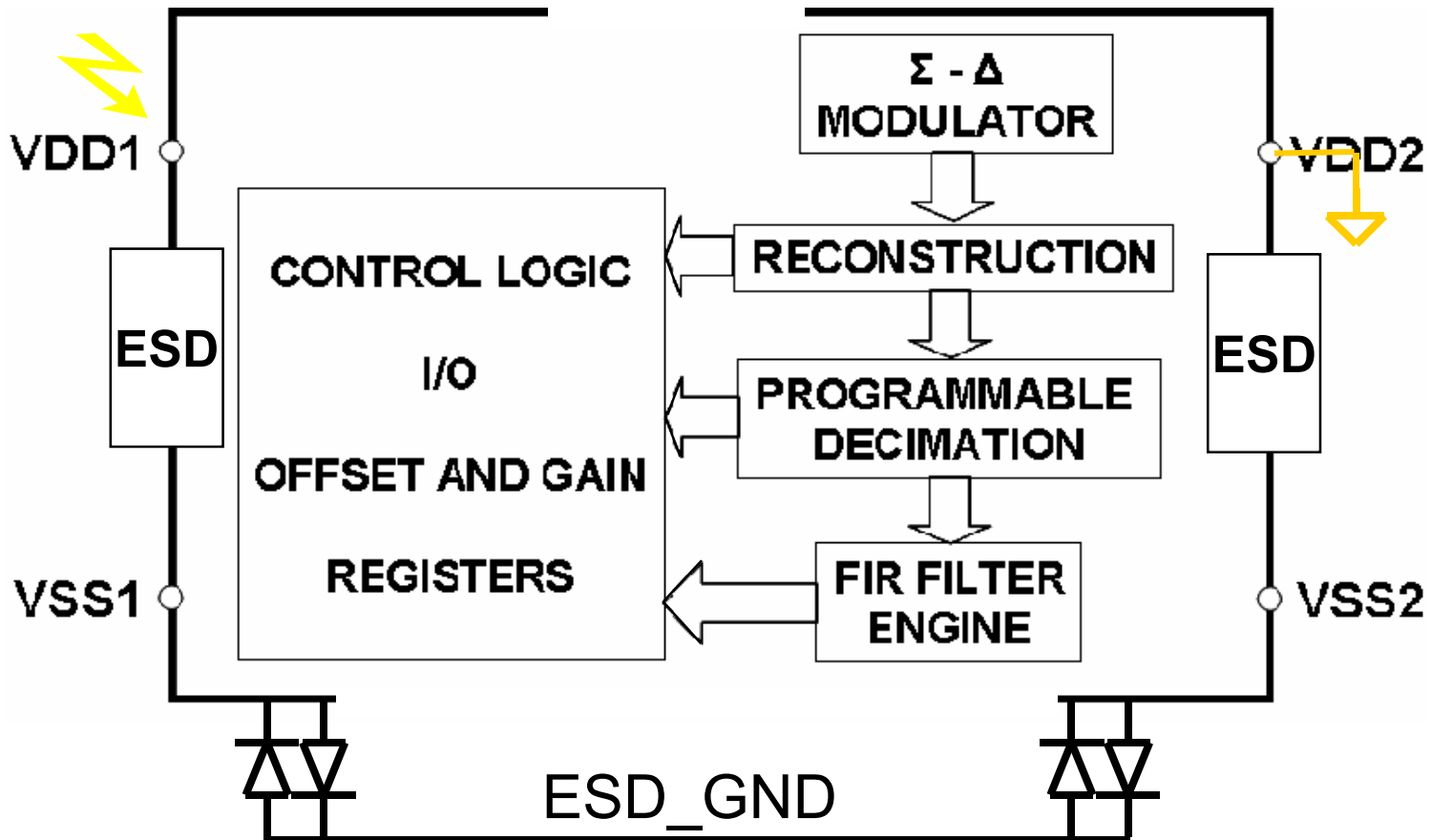
SPICE Simulation Examples

System Level - A 24-bit Σ - Δ converter



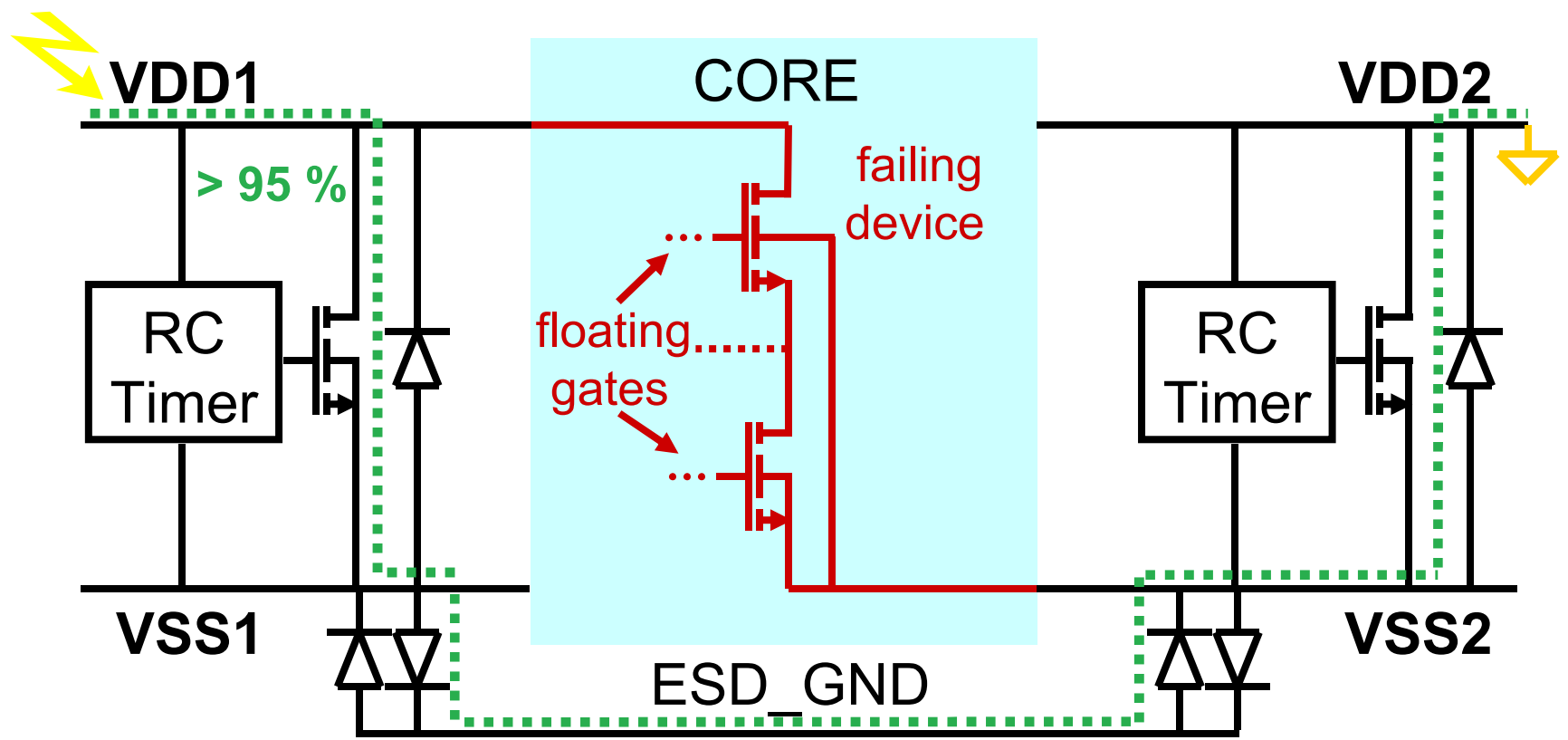
SPICE Simulation Examples

System Level - HBM Stress between VDD1 and VDD2



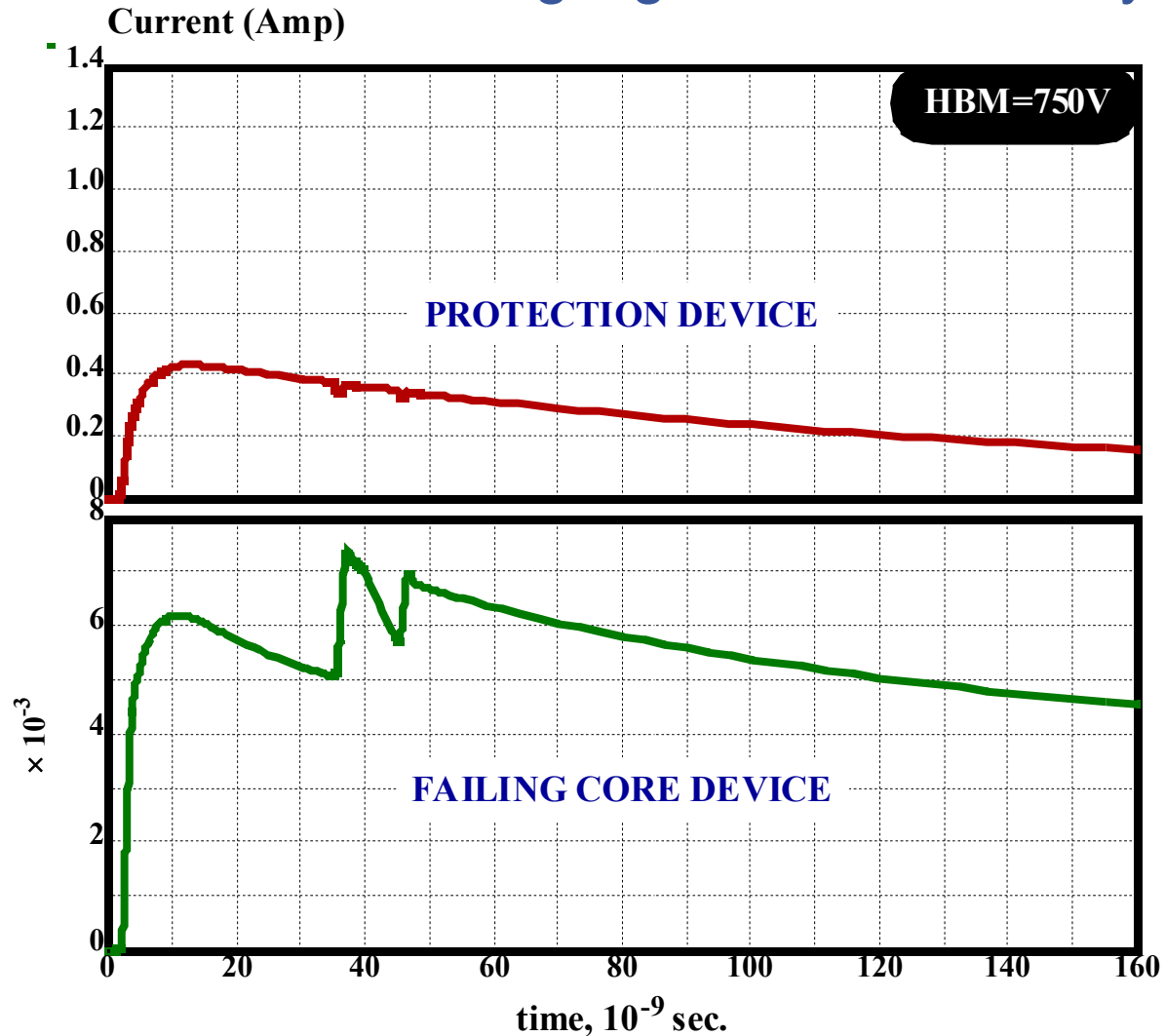
SPICE Simulation Examples

System Level – Original Design Fails 700V HBM



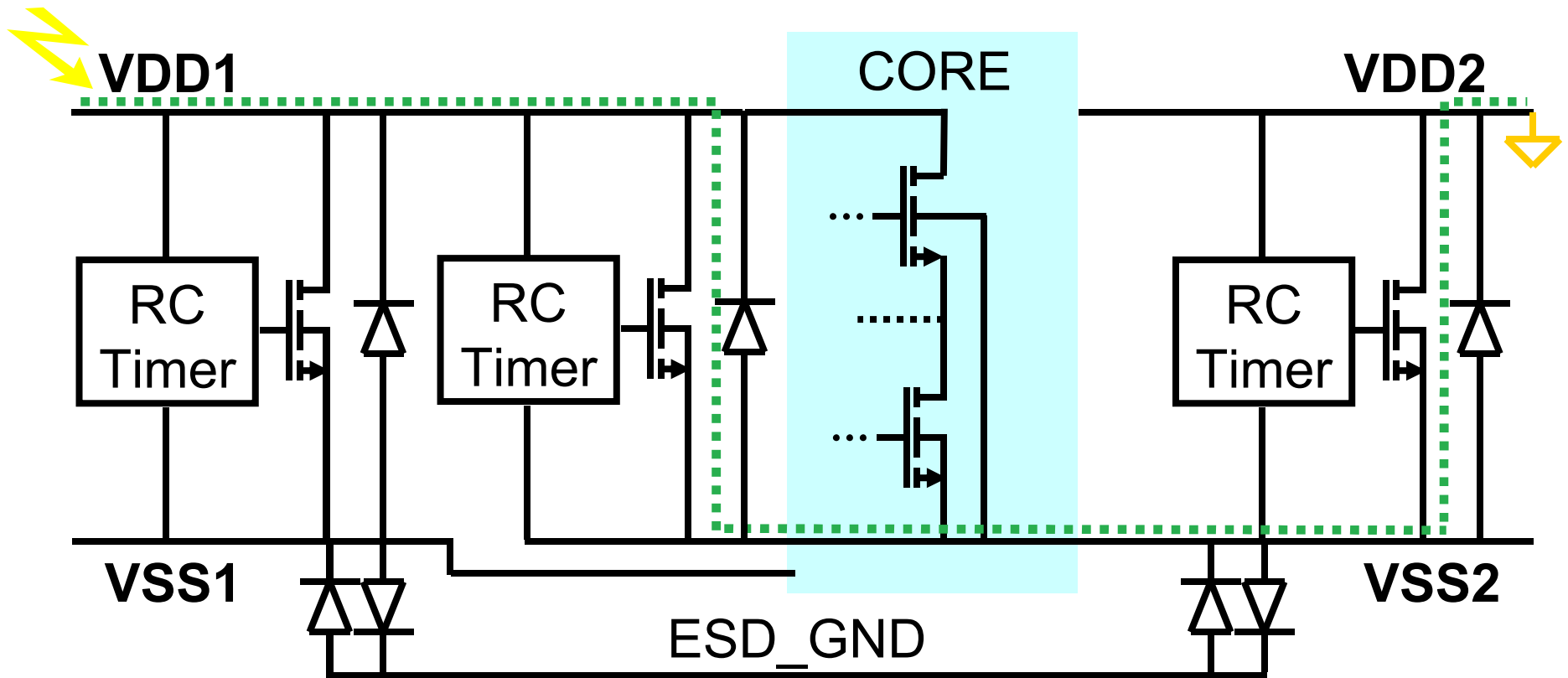
SPICE Simulation Examples

System Level – Simulation Highlights Core Circuitry Failure.



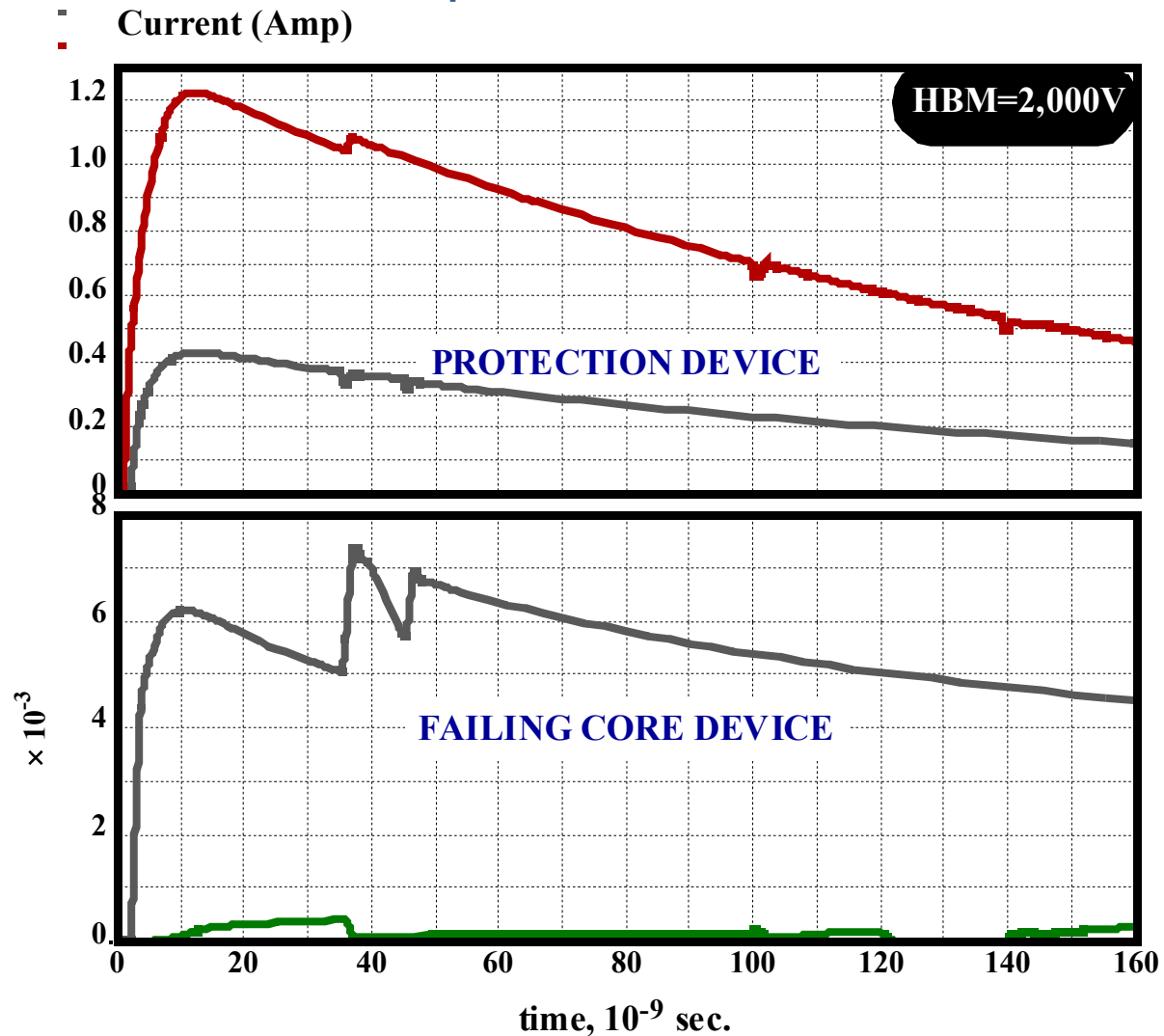
SPICE Simulation Examples

System Level – Revised Design, 2,000V HBM Level Predicted



SPICE Simulation Examples

System Level – Simulation predicts failure above 2,000V HBM





SUMMARY

- ◆ **ESD is an important product reliability concern.**

- ◆ **Compact Modeling approach for accurate modeling of MOS & SCR devices**
 - **Uses Industry standard Models**
 - **Simple Implementation**

- ◆ **Successful SPICE-type circuit simulation of ESD event:**
 - **Design ESD Protection Cells**
 - **Predict ESD Performance**
 - **Confirm and fix known ESD failures**



END